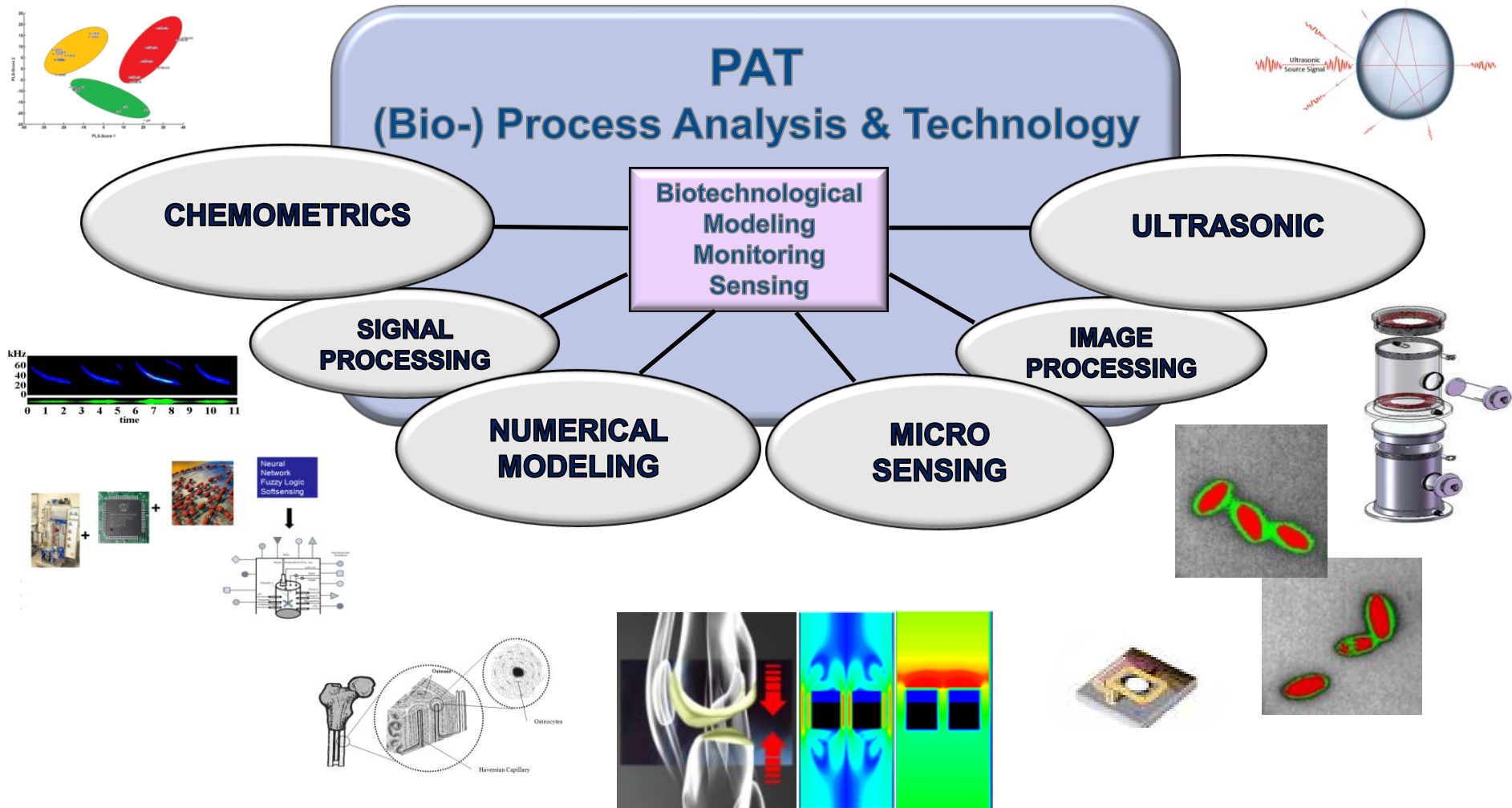


(Bio-) Process Technology, Process Analysis Technology

Hussein, M.





Ultrasonic Measurement Techniques for Process Monitoring using the Example of Concentration Monitoring of Fermentation Fluids

Sven Hoche; M.A. Hussein; T.Becker

→ Requirements for process monitoring sensors:

- **robustness** (pressure, temperature, vibration, shock)
- high chemical **corrosion resistance**
- no **detrimental effect** on the process (contamination)
- **rapid response**
- **low investment and running costs** (minimal maintenance , energy consumption, ...)
- easy **retrofit** for existing plants
- **standardized system integration** - mounting (flanges etc.), communication (output signal: 4–20 mA, Profibus, Fieldbus Foundation)
- conformity with standards (**hygienic standards, standards for electrical apparatus,...**)

→ Advantages:

- ultrasonic techniques are **non invasive**
- applicable **for in-line measurements, even in-situ**
- **low power consumption**,
- robust, **long-term stable** (maintenance free)
- **rapid response**, usually a fraction of a second
- **high resolution accuracy, high-precision measurement**
- no direct medium contact
 - suitable for sterilisation and cleaning in process
 - suitable for use in hazardous environments. . .
- no restrictions regarding optical or electrical properties of the medium
- works in a wide range of temperature and pressure

→ Disadvantages:

- **increase of effort in electronics for high accuracy** and information enhancement (this does not necessarily mean high costs)
- **acoustical transparency** of substances for transmission and some reflection techniques
- ultrasonic measurements are highly disturbed when gas bubbles in liquids are present – **noise, high signal variations**
- only **integral information** along the entire sound path is delivered
- ultrasonic signals tend to be complicated and need relatively **complex signal processing**
- knowledge of the **acoustic properties** of the substances through which the sound is travelling is often necessary
- **increase of the attenuation** of sound with frequency.
- **temperature and pressure dependent** measurement

➤ Ultrasonic Distance Sensors

- distance, position, level
- path
- object structure
- multidimensional recognition
- presence of objects
- process monitoring
- motion, speed, path (Doppler effect)

➤ Impedance Sensor

- density
- acoustic impedance

➤ Ultrasonic Propagation Path Sensor

- concentration of multicomponent systems
- particle size distribution (suspensions, emulsions)
- volume and mass flow velocity
- transmission properties
- temperature measurement
- dynamic pressure measurement

➤ Mass Sensitive Sensors

- mass
- viscosity
- specific chemical or biological species
- multicomponent analysis

➤ **Chemical and pharmaceutical industry:**

- Polymerisation
- Galvanic
- Lacquers and paints
- Waste water treatment

➤ **Biotechnology:**

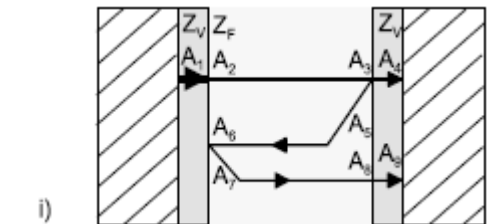
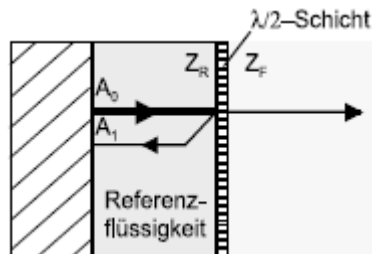
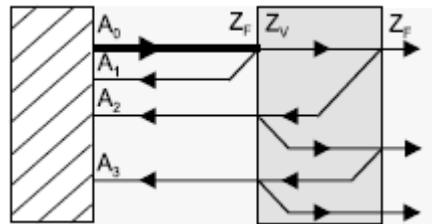
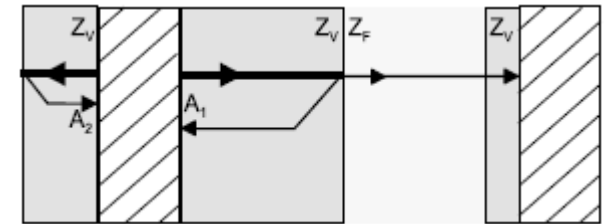
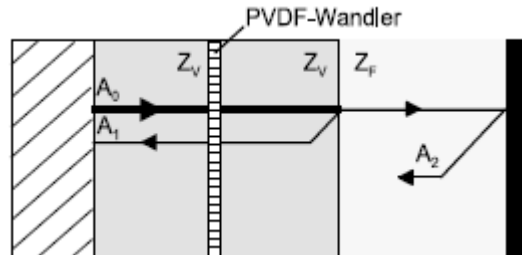
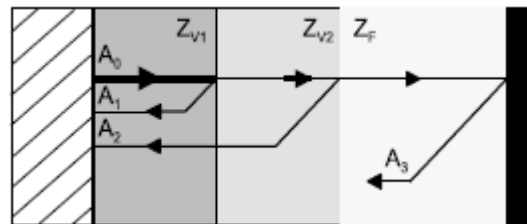
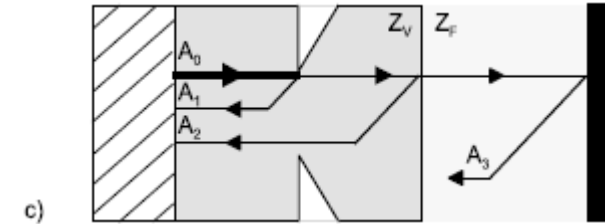
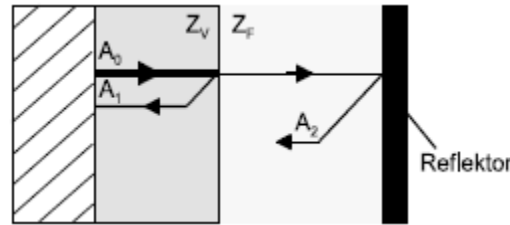
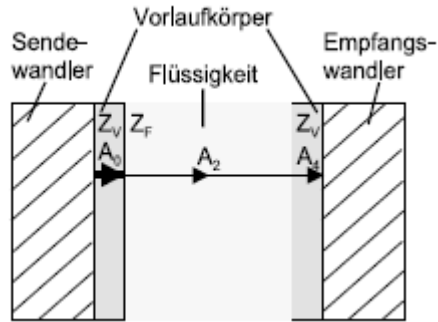
- Alcoholic or lactic acid fermentation
- Enzyme concentration

➤ **Food industry:**

- Beverage industry
- Starch production
- Margarine production
- Dairy industry

➤ **General other application**

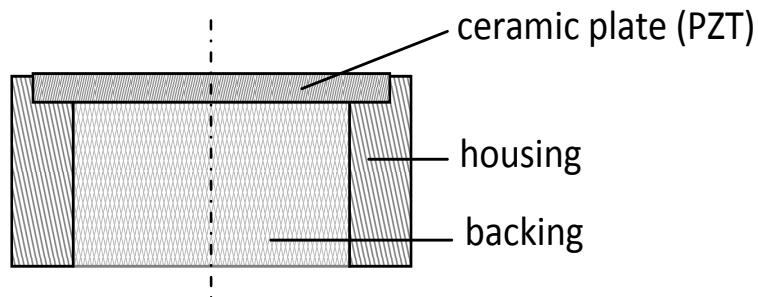
- particle/ bubble size
- rheological properties



- Piezokeramik
- Verlauf-, Referenzkörper (Festkörper)
- Flüssigkeit
- Referenzflüssigkeit
- Reflektor

- a) Hale
- b) McClements
- c) Jensen
- d) Fischer
- e) Adamowski
- f) Püttmer
- g) Kline
- h) Hirnschrodt
- i) Henning (Hale)

- **In-Line-Monitoring (Control)** of sugar and ethanol concentration as important indicators for the status of alcoholic yeast fermentation processes.
- Current Work: Optimization and validation of an **ultrasound based inline sensor system**.
- **Principle:** pulse-echo; impulse generation (dirac impulse: 0-100 V, $2.5E-7s$), signal processing and data transfer via data acquisition system.



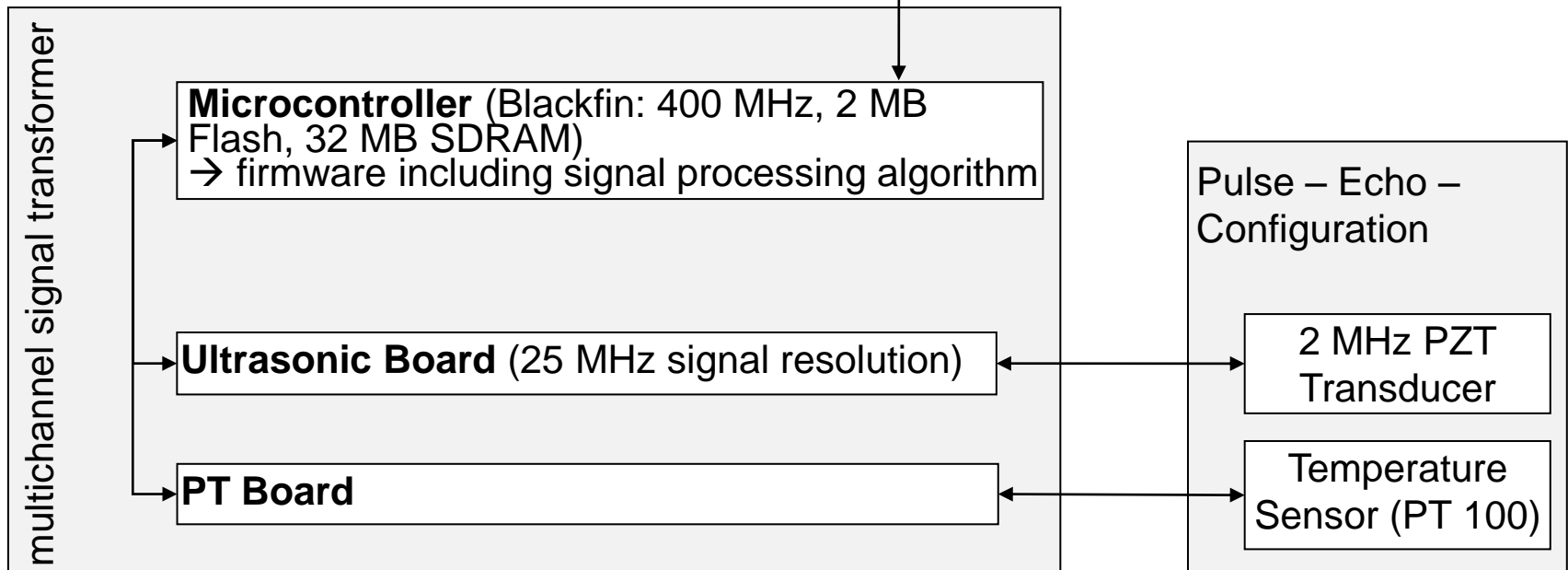
Process Control System

Field Bus Communication
(PROFIBUS)

Process
Control Center

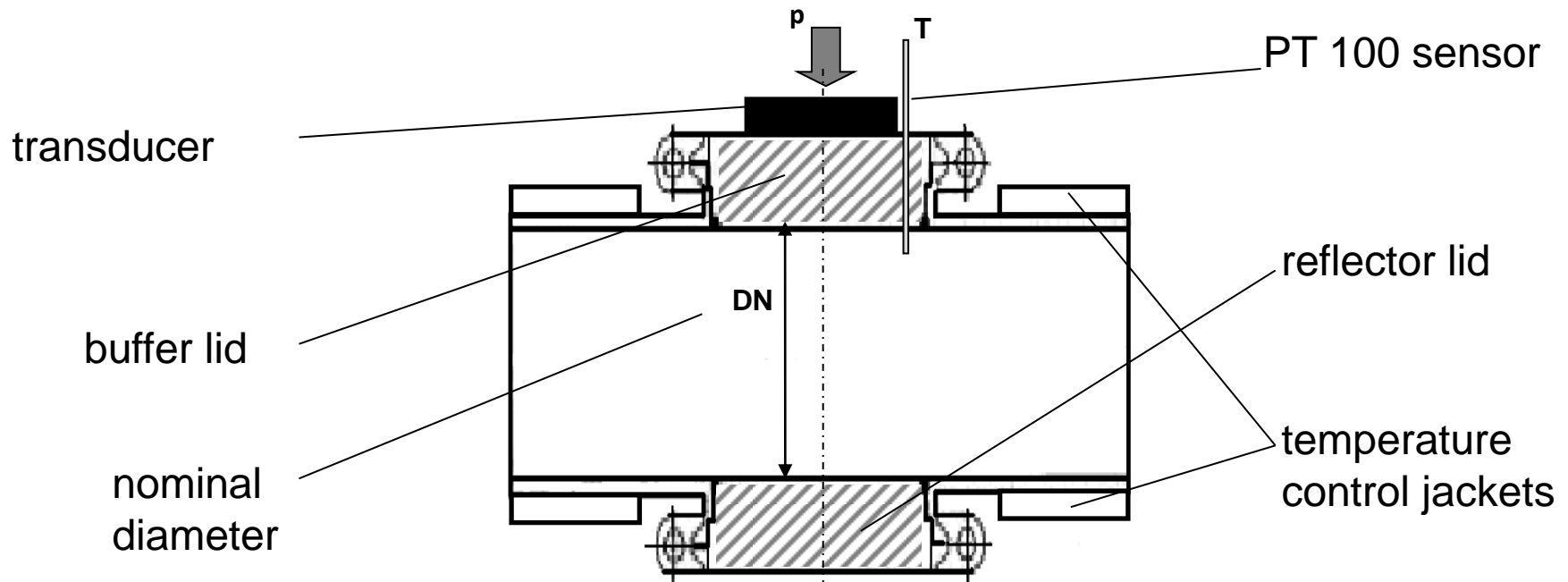


Sensor Settings
Signal Processing Settings
Process Information (T, TOF,...)

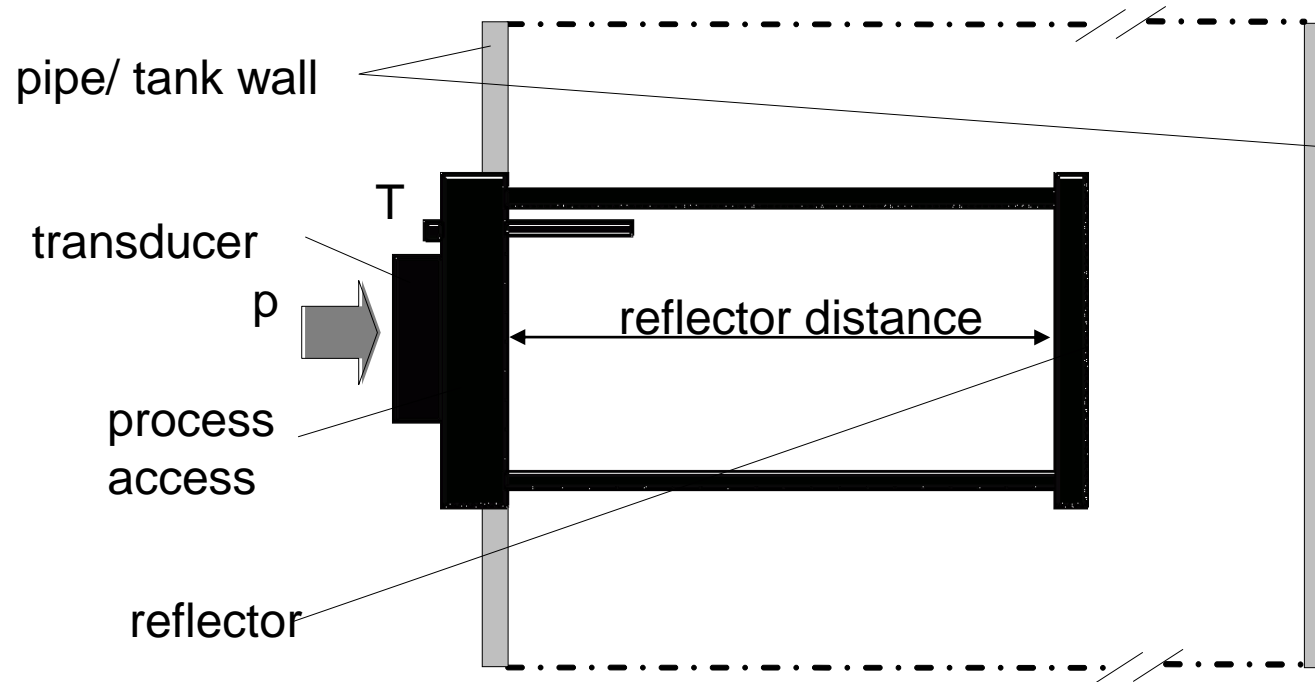


→ pulse-echo setup based on a VARINLINE® access unit (typical process access for inline sensors in food industries, stainless steel)

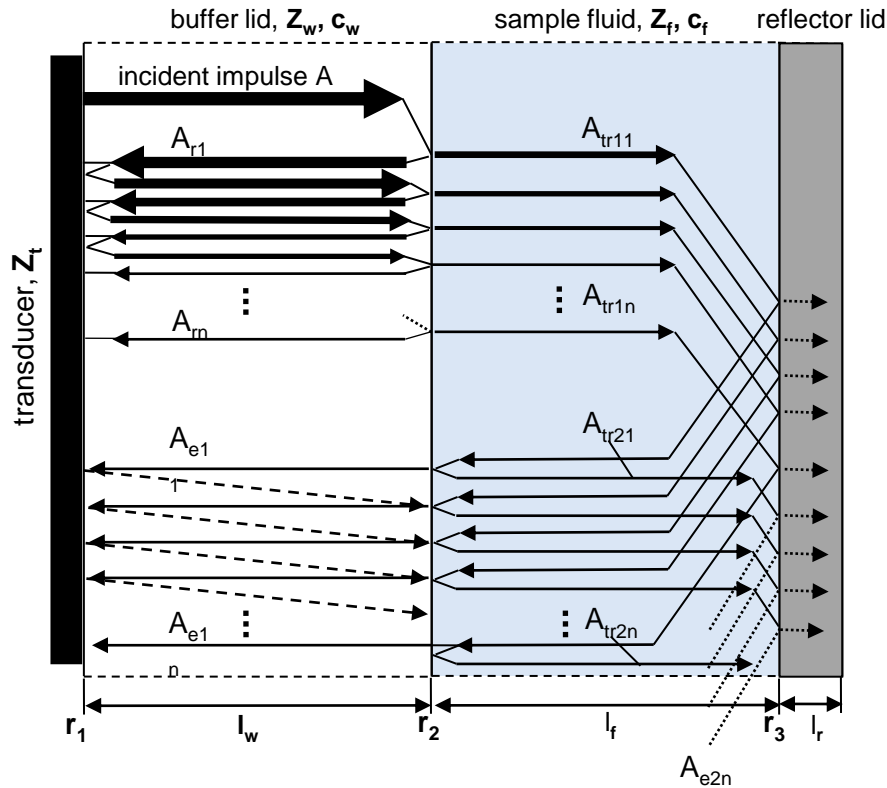
→ two nominal diameters were used, 50 mm (DN50) and 80 mm (DN80) (defines the approximate propagation path for the signal)



- pulse-echo setup based on a VARINLINE® access unit
- adjustable reflector distance, current 70 mm



Puls-Echo-Method



where:

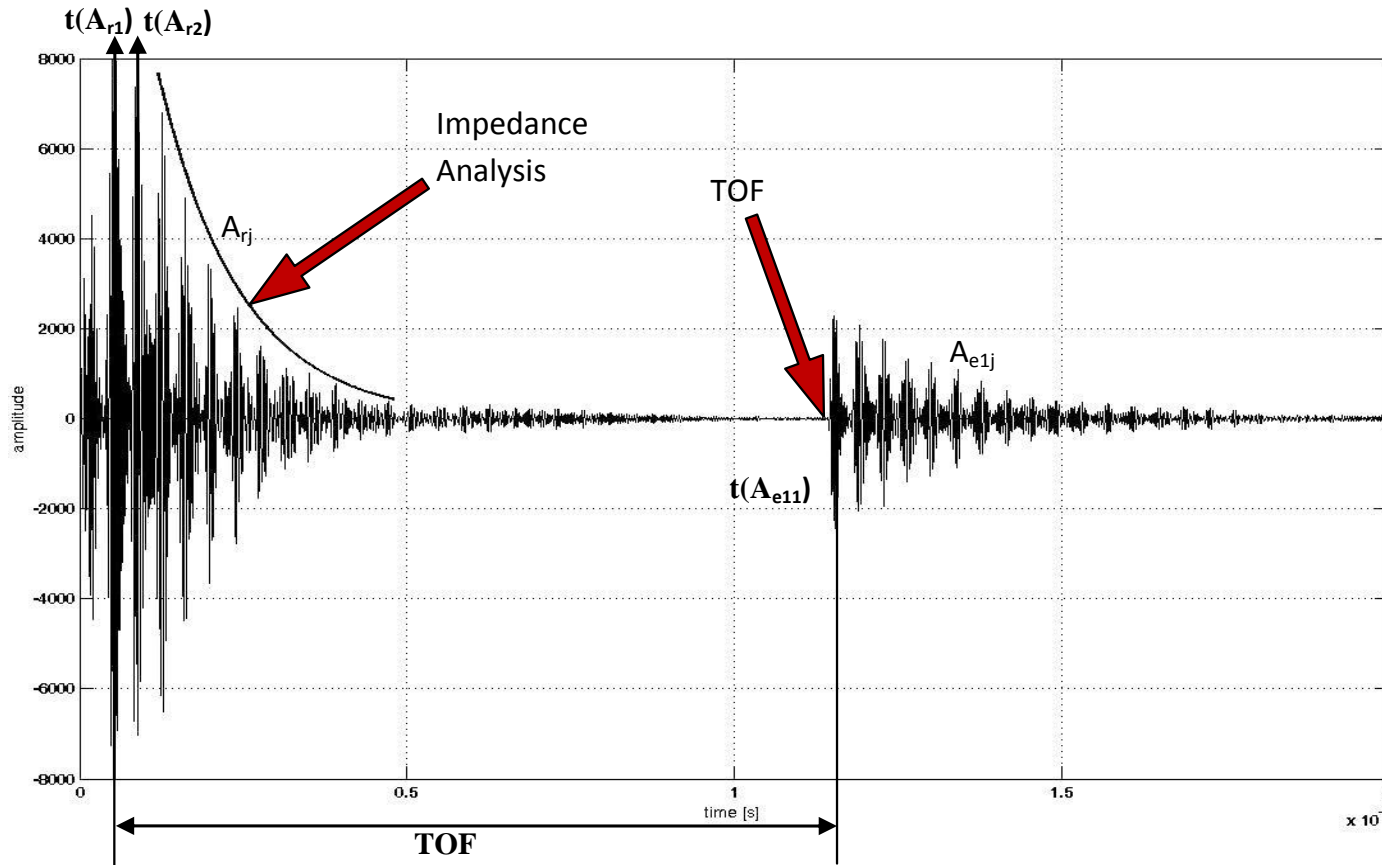
A_m : from interface buffer fluid reflected impulse pulses, traveling from interface buffer-fluid to fluid-reflector
 A_{trjn} : echoes from fluid-reflector interface

Z : medium impedance
 c : medium USV

r_1 : reflection coefficient of transducer-buffer interface
 r_2 : reflection coefficient of buffer-fluid interface
 r_3 : reflection coefficient of fluid-reflector interface

j : index for the echo
 n : index for single pulses inside a set of multiple reflections

- Impedance from reflections inside buffer
- USV from echo (reflector)

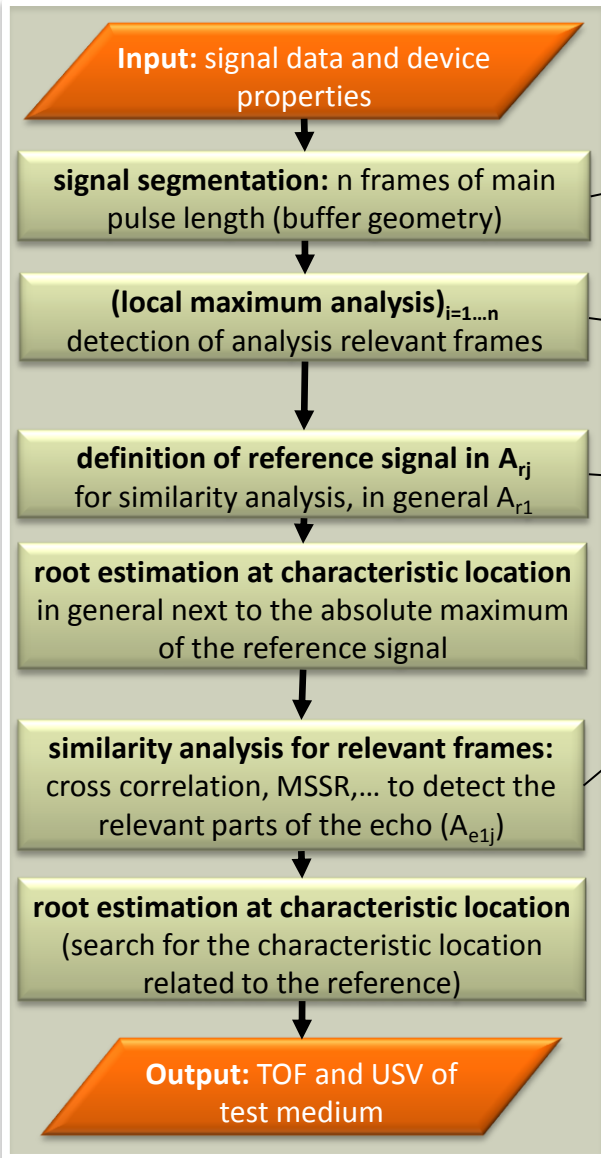


→ Exponential Decay of Buffer Reflections:

$$A_n = A \cdot r_1^n \cdot r_2^{n-1} \cdot \exp(2 \cdot n \cdot \alpha_1 \cdot l_w)$$

→ Time of Flight (TOF):

$$TOF = t(A_{e11}) - t(A_{r1})$$



frame definition due to known setup values
 → wall thickness (wt), wall material (wc)
 $\text{frame time} = \text{sf} \cdot (2 \cdot \text{wt}) / \text{wc}$ sf...safety factor (due to material variations)

frame wise maximum amplitude analysis
 global threshold method to reduce analysis

constant constraints

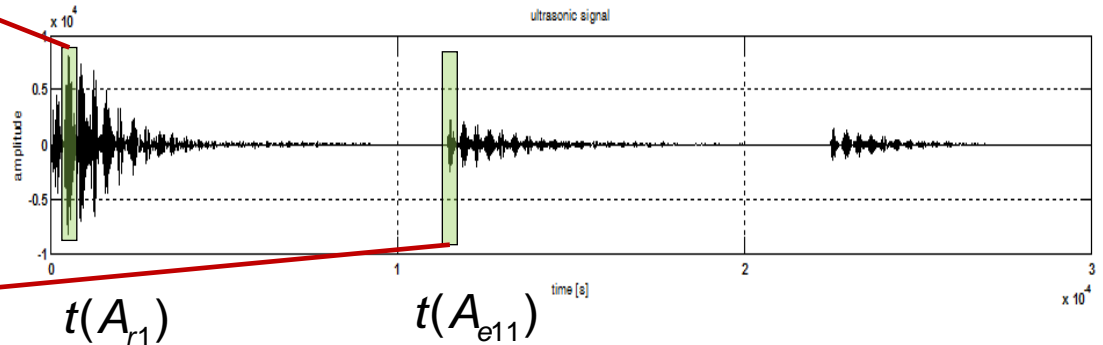
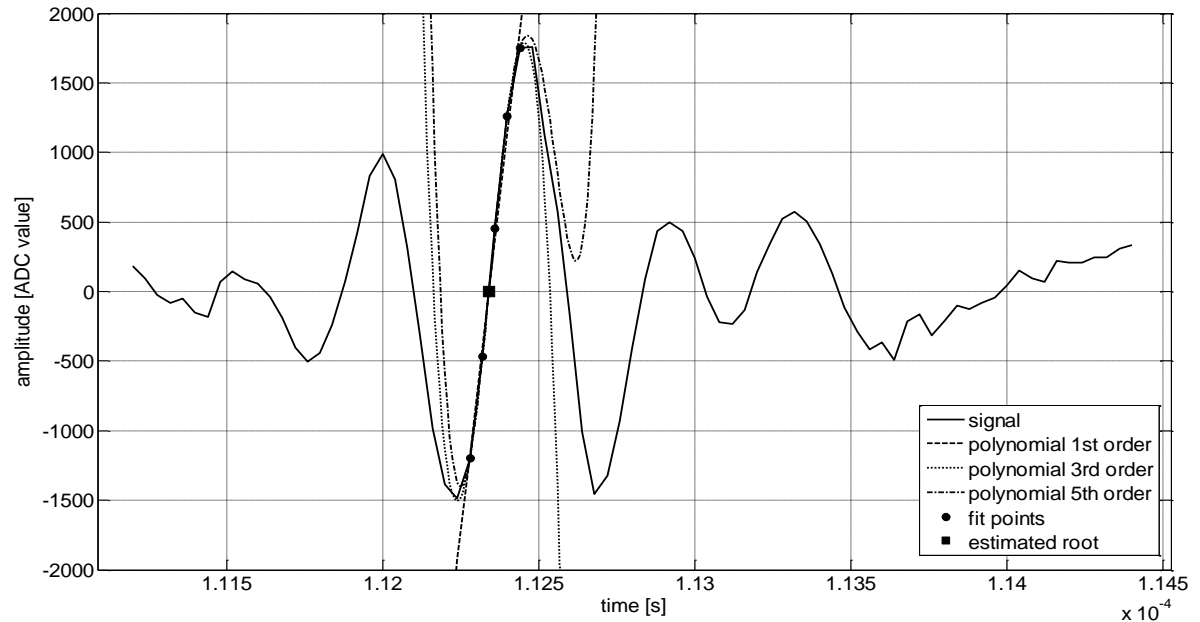
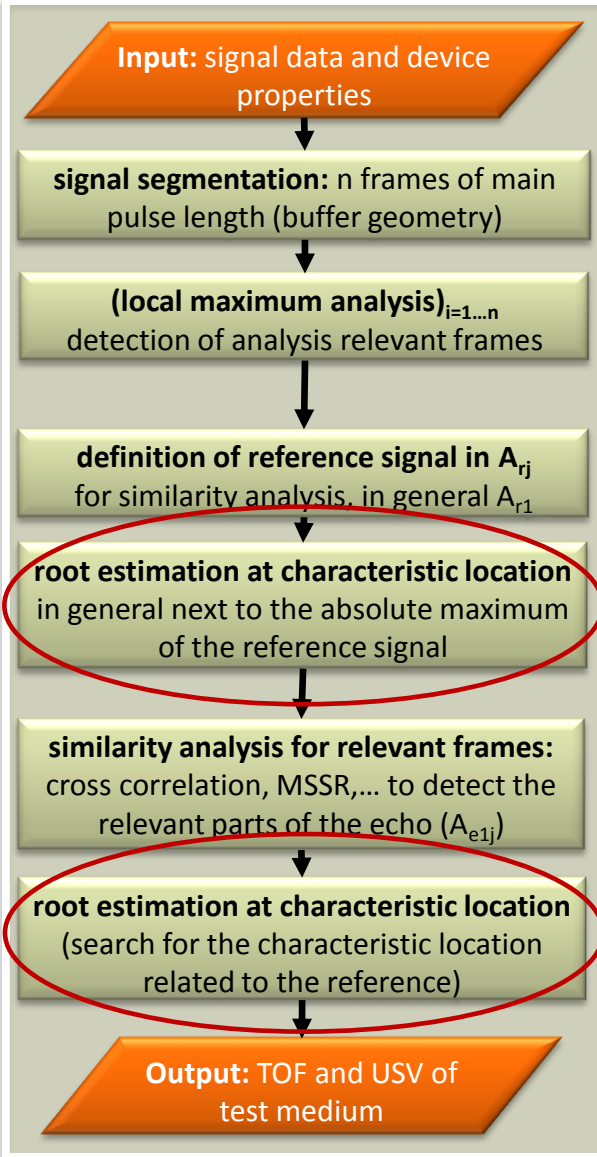
Bivariate Time Series Analysis:

Mean Square Sum of Residuals

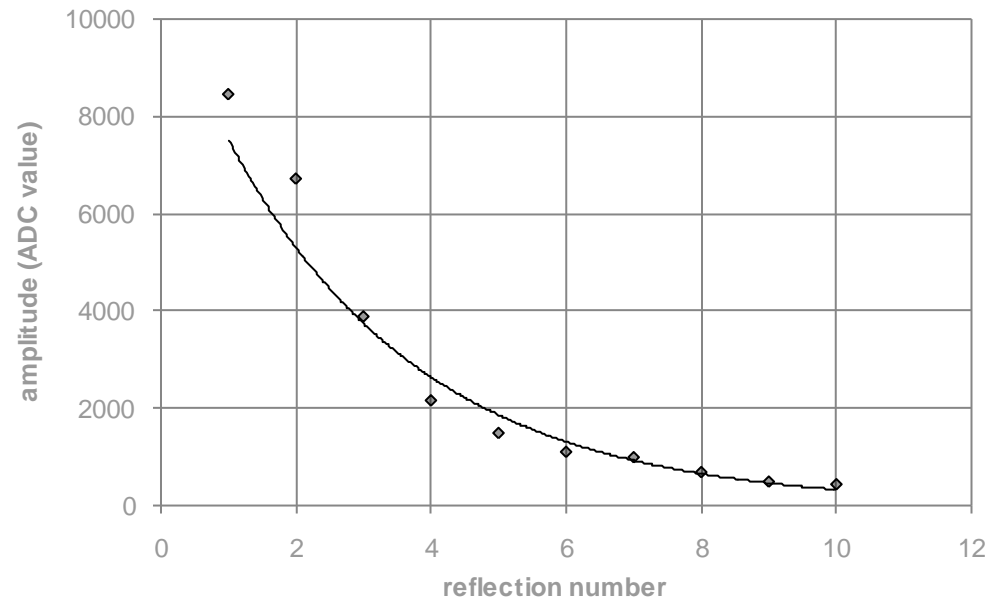
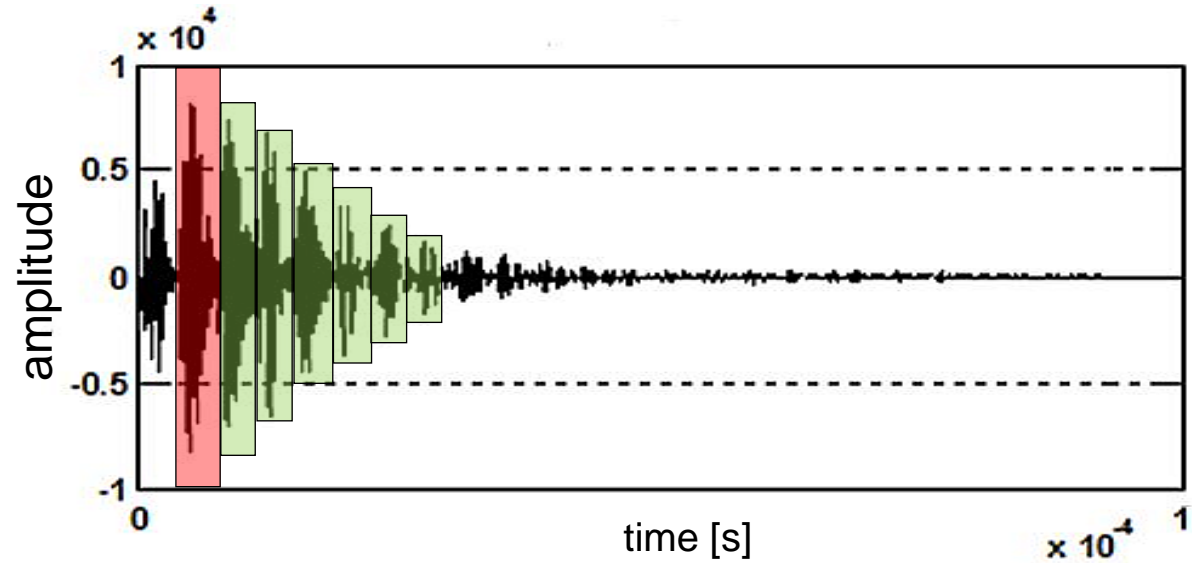
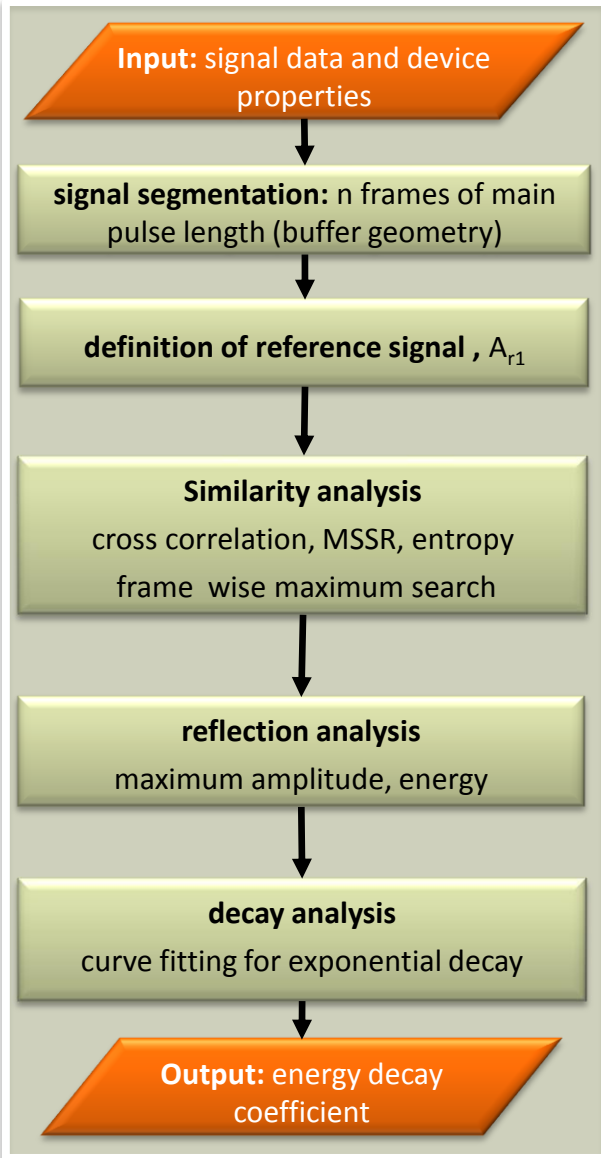
$$\text{MSSR}(k) = \frac{\sum_i^n |A_{\text{reference}}(k+i) - A_{\text{frame}}(k+i)|}{n}$$

Cross Correlation

$$\text{corr}(k) = \frac{\sum_i^n [A_{\text{reference}}(k+i) * A_{\text{frame}}(k+i)]}{n}$$



$$TOF = t(A_{e11}) - t(A_{r1})$$



→ exponential decay

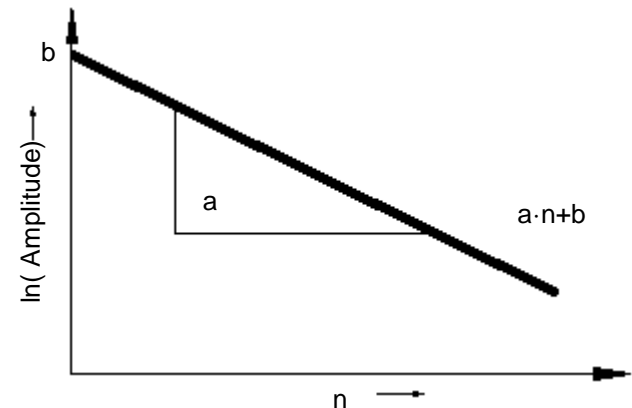
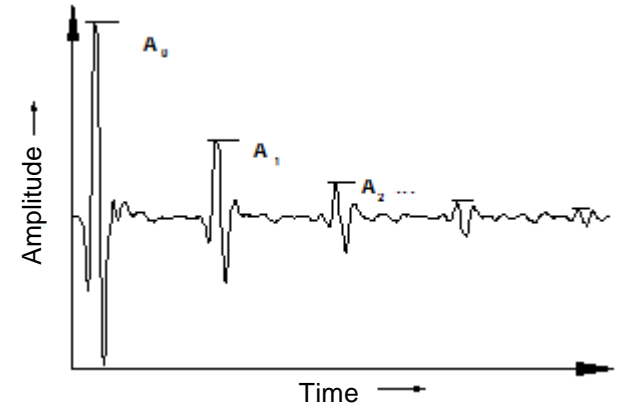
$$A_n = A \cdot r_1^n \cdot r_2^{n-1} \cdot \exp(2 \cdot n \cdot \alpha_1 \cdot l_w)$$

$$\begin{aligned} \ln A_n &= [\ln r_1 + \ln r_2 + 2 \cdot \alpha_1 \cdot l_w] \cdot n + [\ln A - \ln r_2] \\ &= a \cdot n + b \end{aligned}$$

→ comparison of exponential slopes

$$\frac{e^{a_{\text{sample}}}}{e^{a_{\text{reference}}}} = \frac{r_1 \cdot r_{\text{sample}} \cdot e^{2 \cdot \alpha_1 \cdot l_w}}{r_1 \cdot r_{\text{reference}} \cdot e^{2 \cdot \alpha_1 \cdot l_w}}$$

$$r_{\text{sample}} = r_{\text{reference}} \cdot e^{(a_{\text{sample}} - a_{\text{reference}})} = \frac{r_{\text{reference}}}{e^{(a_{\text{reference}} - a_{\text{sample}})}}$$



→ impedance Z:

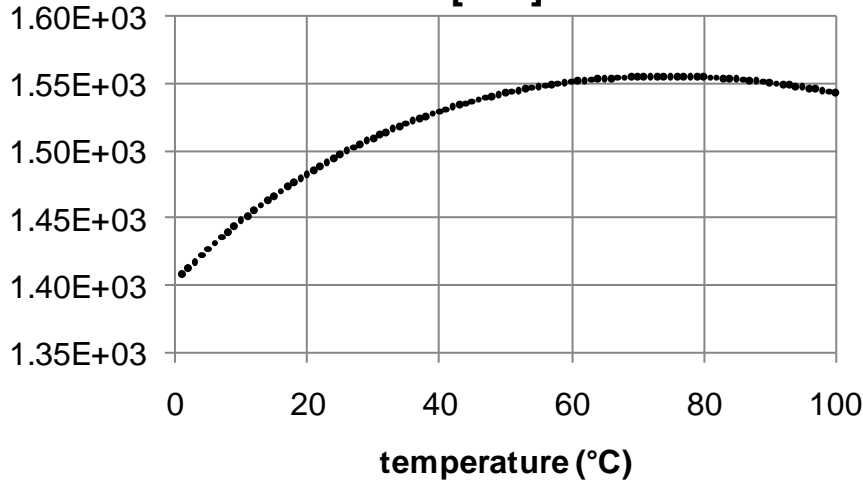
$$Z_{\text{sample}} = Z_{\text{steel}} \cdot \frac{1 - r_{\text{sample}}}{1 + r_{\text{sample}}}$$

→ density ρ

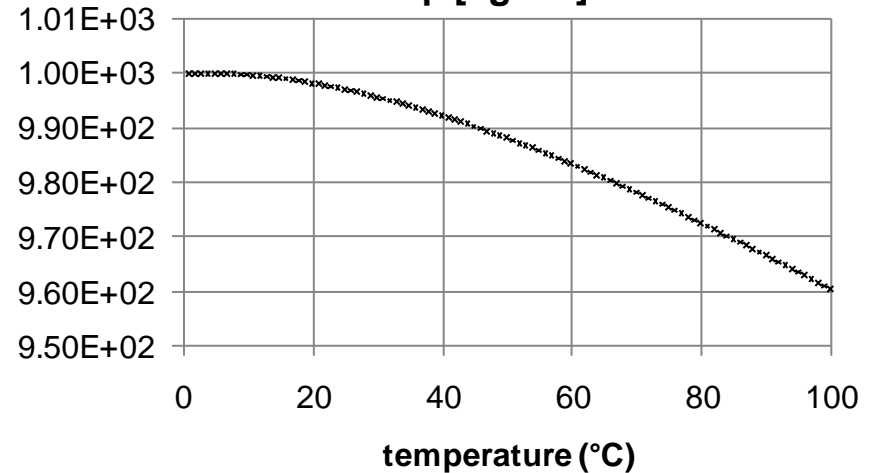
$$\rho = \frac{Z}{USV}$$

→ Ideal reference material is **demineralized, vented water**.

USV [m/s]

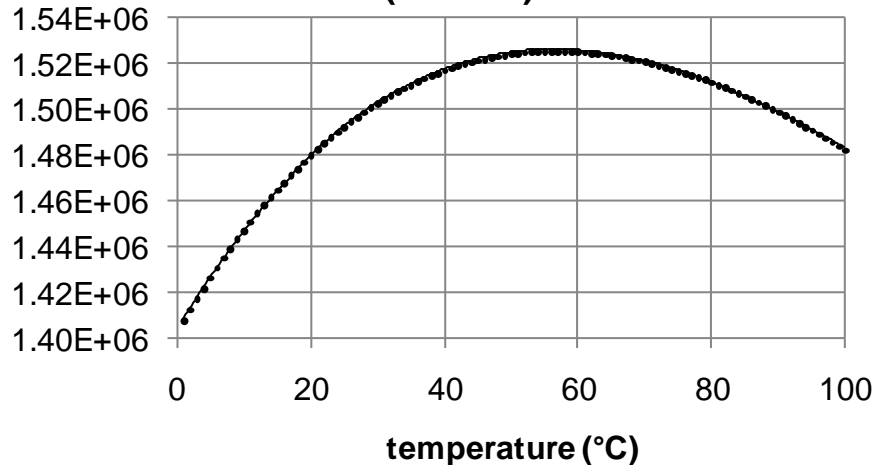


ρ [kg/m³]



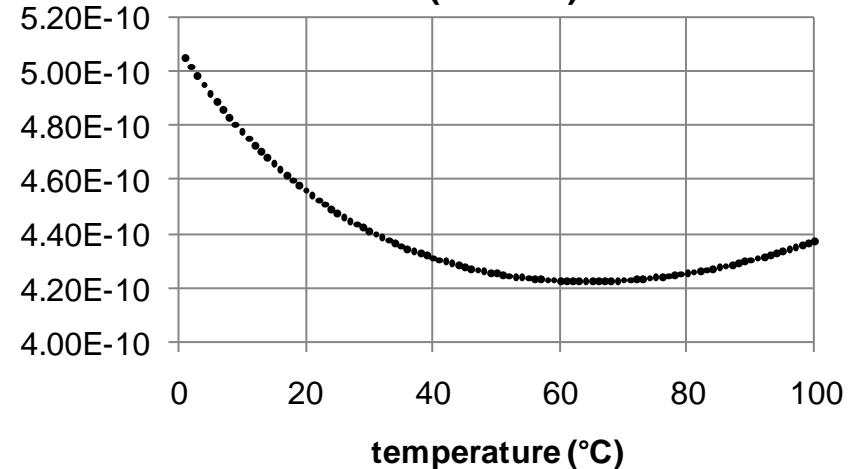
$$Z = USV \cdot \rho$$

Z (N*s/m³)



$$\kappa = USV^2 \cdot \rho^{-1}$$

κ (N*s/m³)



→ For an **independent model** the TOF has to be related to the **passed distance in the medium (l_f)** and their changes due to **thermal expansion**.

→ Since $t(A_{e11})$ is determined from the **echo** the TOF-analysis is **influenced by signal variations** caused by disperse parts of the fermentation medium (bubbles of different size, disperse particles,...).

→ TOF-analysis accuracy is dependent on the **time resolution** of the captured data and the **stability** of the used methods to the signal variations.

→ High **requirements** for accurate, high resolution concentration models for USV-measurements:

- Assuming a water-sugar-mixture of 10°C a sugar consistency change from 1% to 2% would cause an approximate **difference of 3 m/s in USV**
- This means, assuming an aimed process monitoring resolution of 0.01% sugar content a standard deviation less than **0.015 m/s USV** or approximate **1 ns TOF** should be achieved.

→ **Targets:** Sugar and ethanol concentration monitoring resolution of **0.05 %**:

- maximum USV standard deviation of **0.075 m/s**
- maximum TOF standard deviation of **3.5 ns (100 mm distance)**

$$\Delta c(USV, T) = \frac{\partial c}{\partial USV} \cdot \Delta USV + \frac{\partial c}{\partial T} \cdot \Delta T$$

$$\Delta USV(TOF, T) = \frac{\partial USV}{\partial TOF} \cdot \Delta TOF + \frac{\partial USV}{\partial T} \cdot \Delta T$$

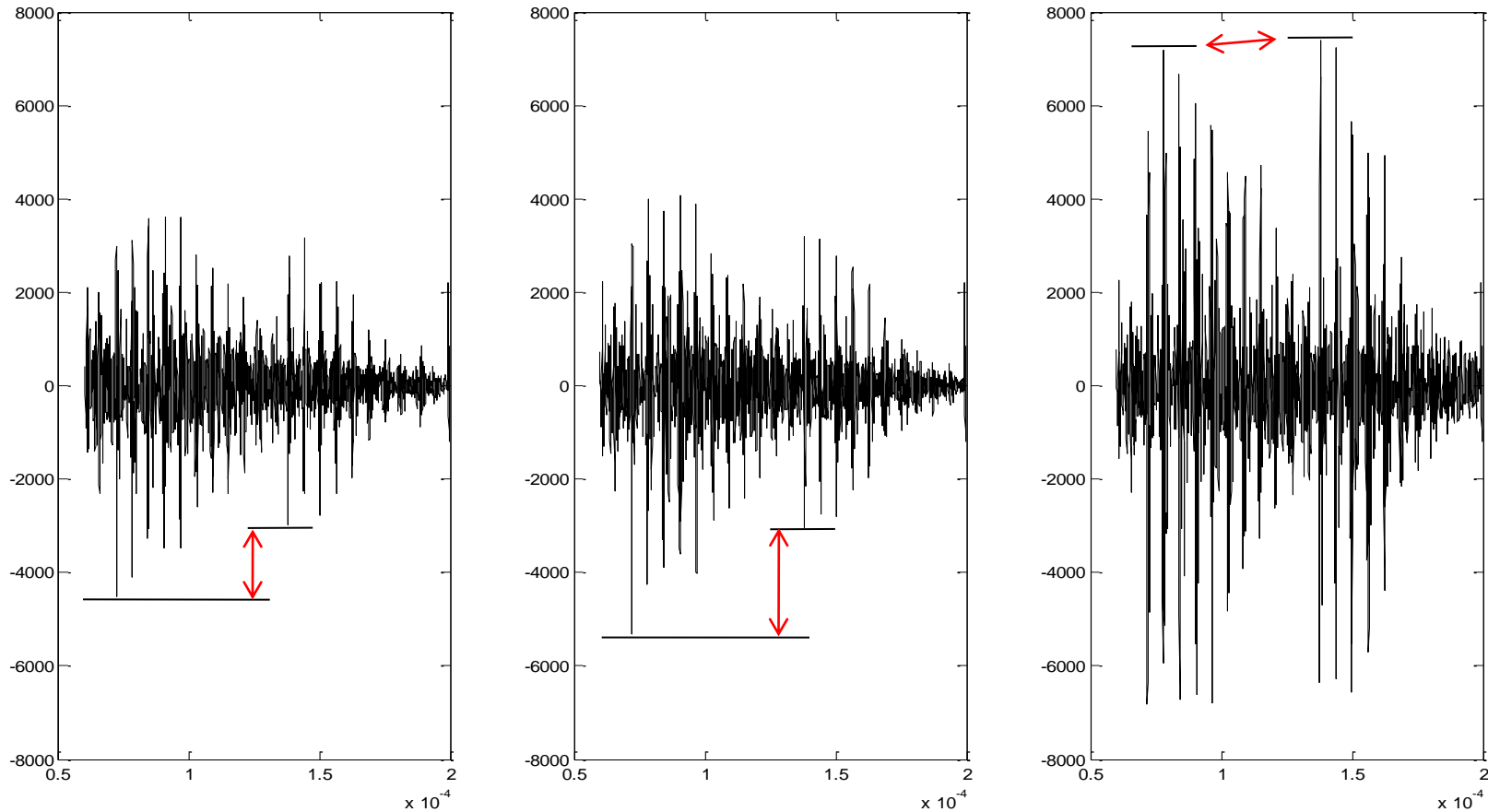
$$USV(TOF, T) = \frac{l(T)}{TOF}$$

$$l = a + b \cdot T$$

$$\frac{\partial USV}{\partial TOF} = \frac{b}{TOF}$$

$$\frac{\partial USV}{\partial T} = \frac{\partial USV}{\partial l} \cdot \frac{\partial l}{\partial T}$$

$$\Delta USV(TOF, T) = \frac{a + b \cdot T}{TOF^2} \cdot \Delta TOF + \frac{b}{TOF} \cdot \Delta T$$



- ultrasonic measurements are highly disturbed when gas bubbles in liquids are present – **variation of absolute value and order**
- sampling frequency restriction: 40 ns

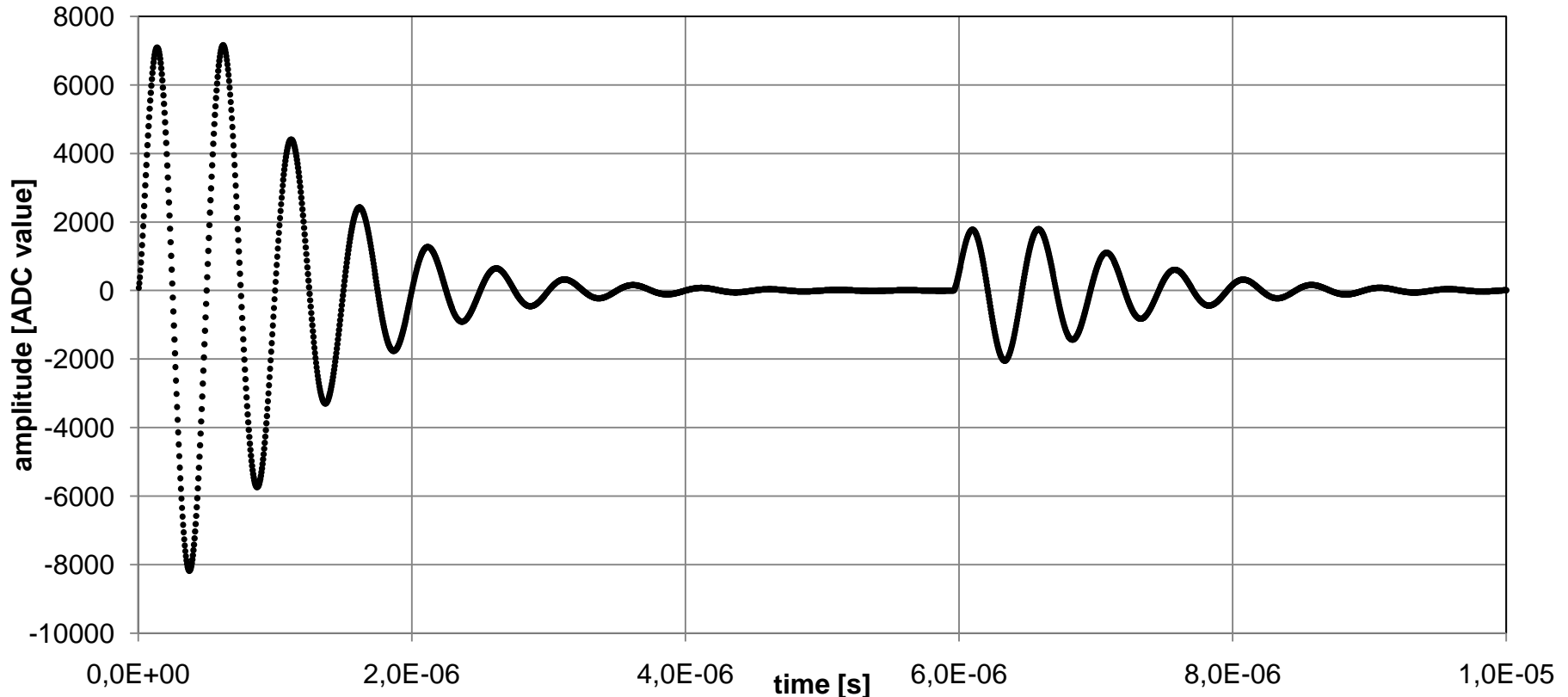
$$A_{exc}(t) = A_{exc0} \cdot e^{(-t/u)} \cdot t^m \cdot \sin(2 \cdot \pi \cdot f \cdot t + \varphi)$$

$$A_{echo}(t) = \alpha \cdot A_{exc} \rightarrow \text{shift of time axis } t_{echo} = t + TOF$$

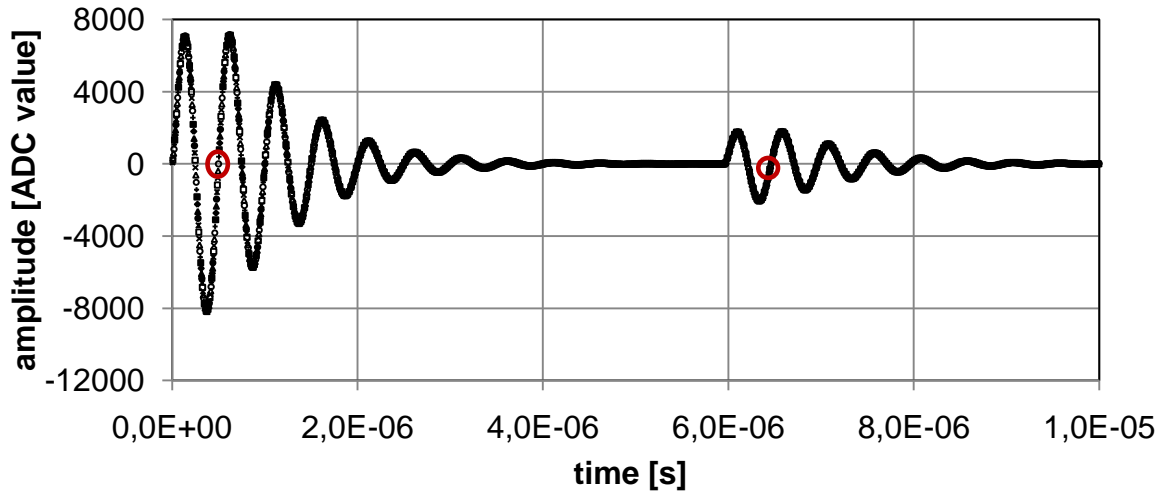
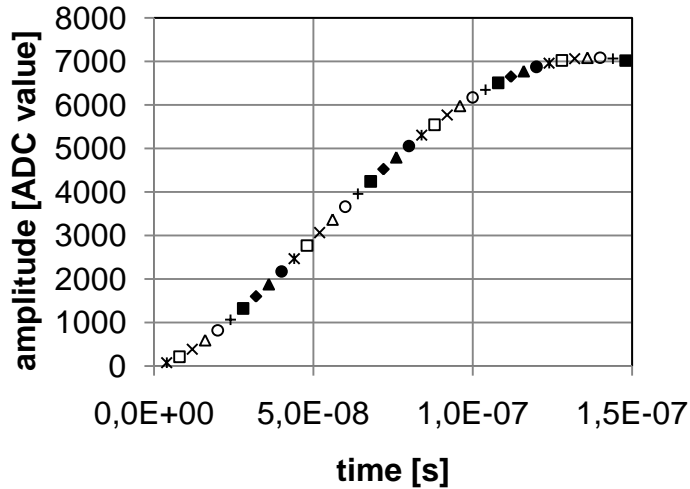
$$A_{signal}[t_0, \dots, TOF] = A_{exc}(t)$$

$$A_{signal}[TOF, \dots, end] = A_{exc}(t) + A_{echo}(t - TOF)$$

excitation amplitude	Ae	2.40E+07
excitation phase	phie	0
excitation frequency	fe	2.00E+06
% shape paramter	m	0.5
	u	16*4E-8
echo amplitude	Ar	6.00E+06
echo phase	phir	0

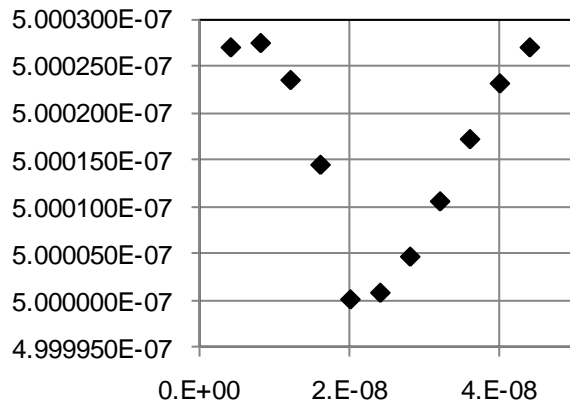


→ 1st time resolution problem: jitter (max. 3 ns)

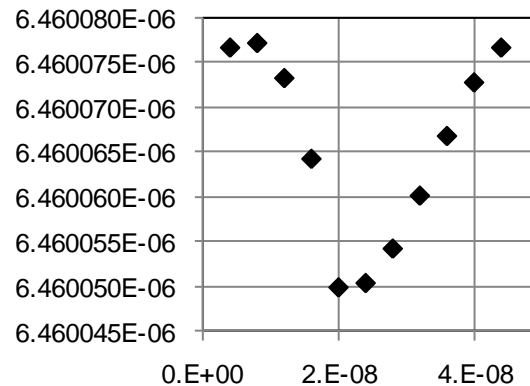


- * 4.00E-09 □ 8.00E-09 × 1.20E-08 △ 1.60E-08
- 2.00E-08 + 2.40E-08 ■ 2.80E-08 ◆ 3.20E-08
- ▲ 3.60E-08 ● 4.00E-08

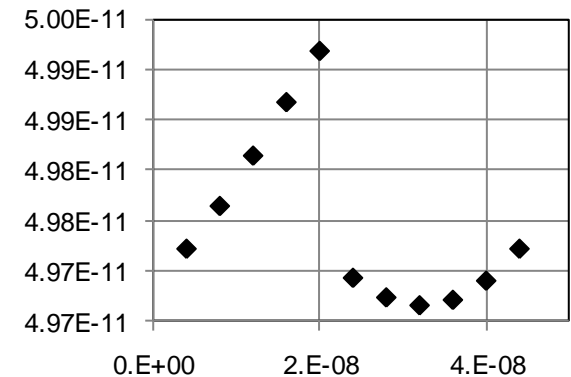
1st root



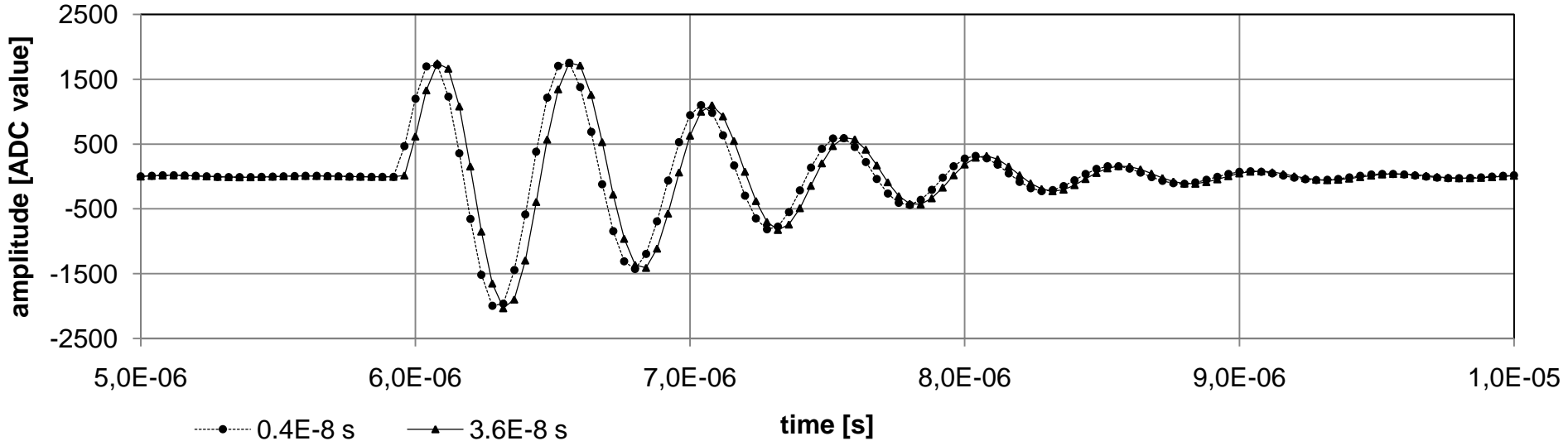
2nd root



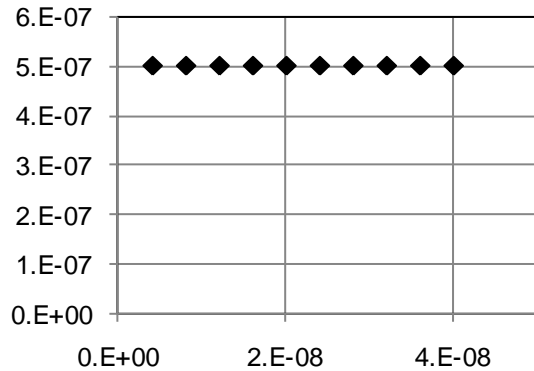
TOF - Variation



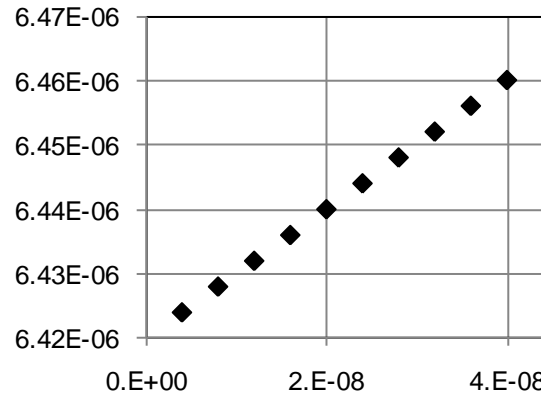
→ 2nd time resolution problem: change of echo



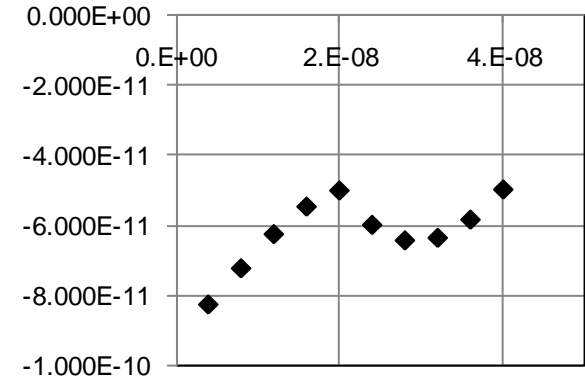
1st root

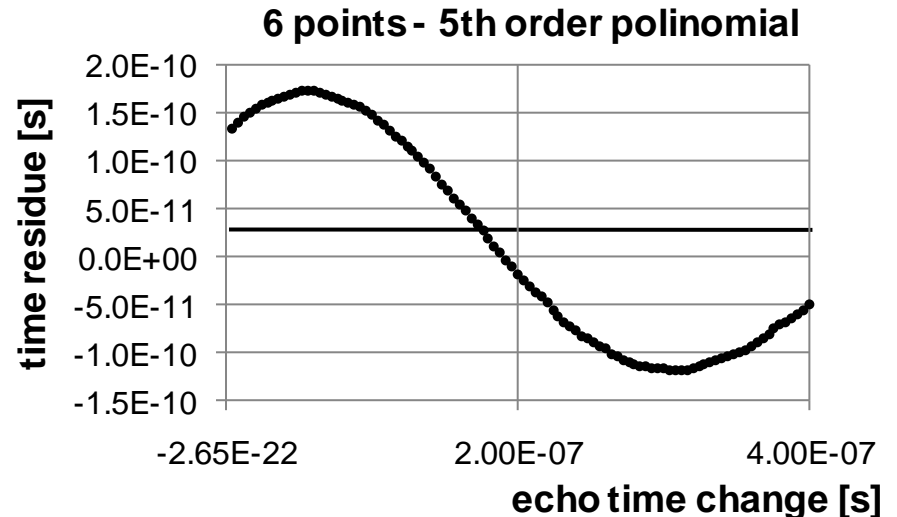
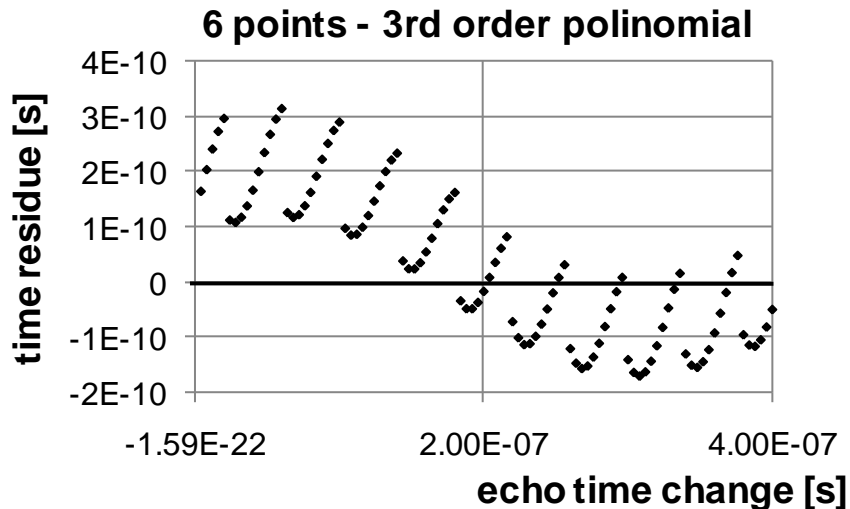
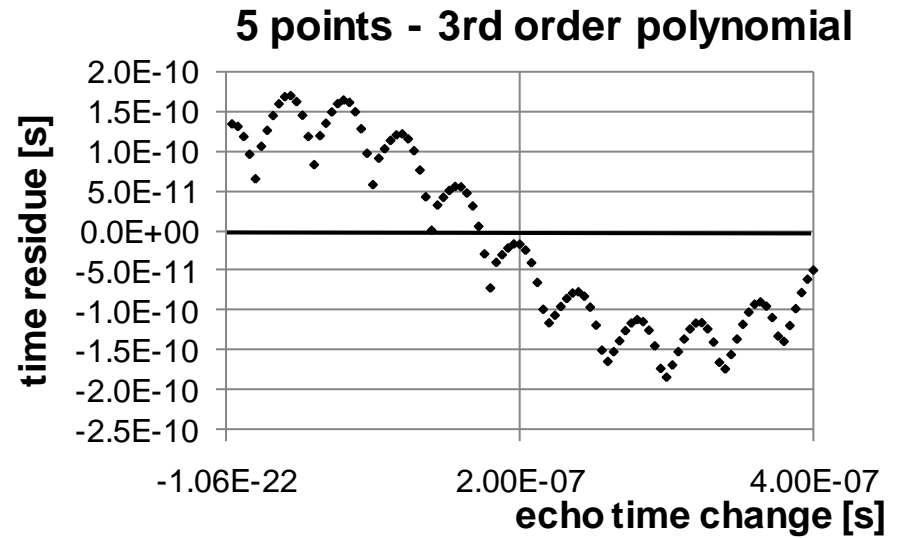
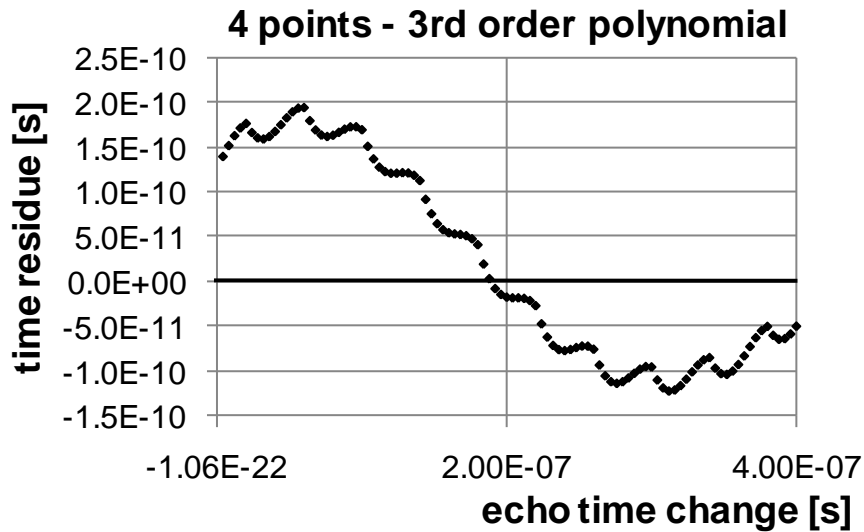


2nd root

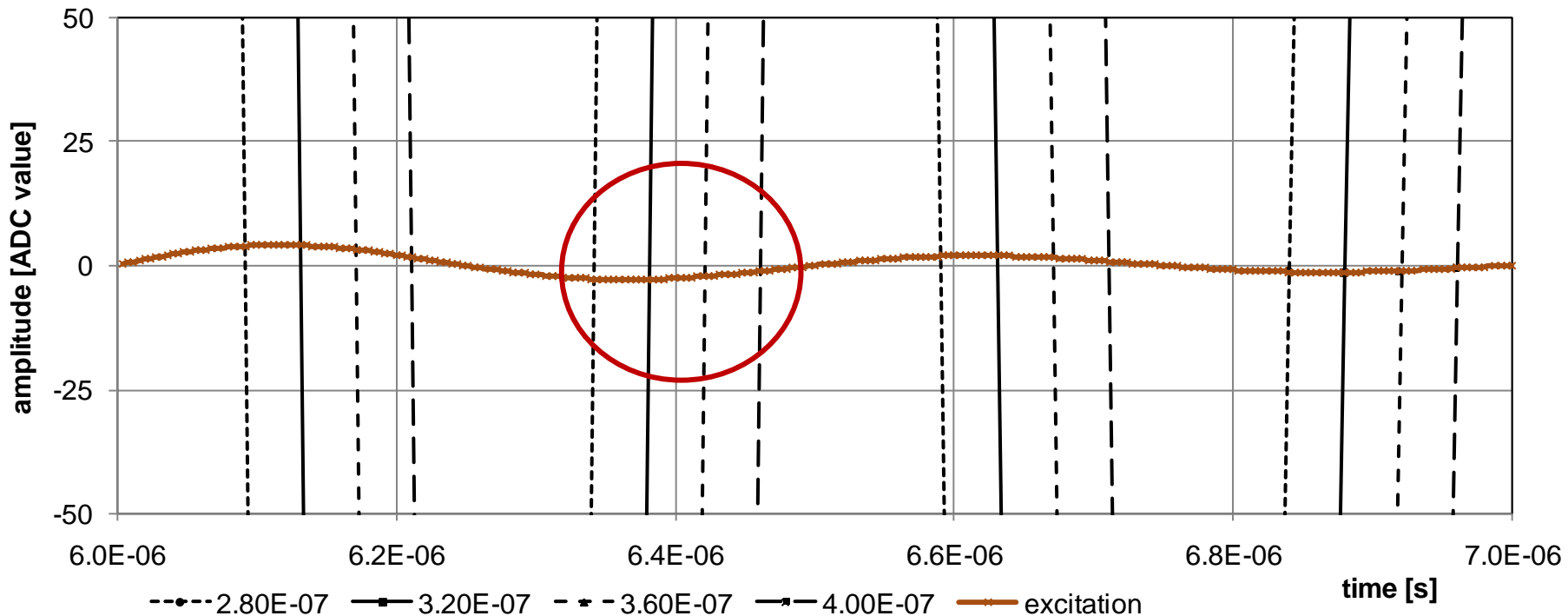
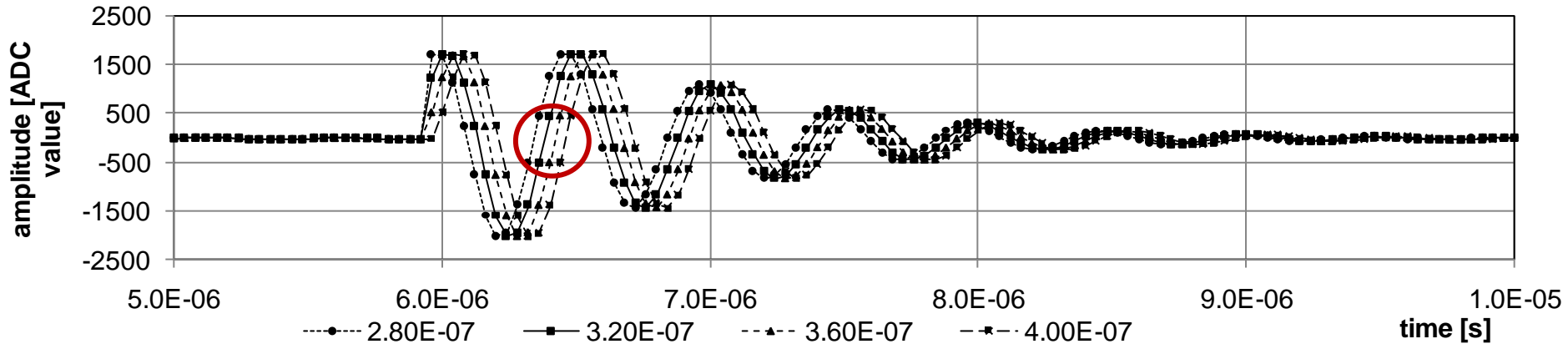


TOF - Variation





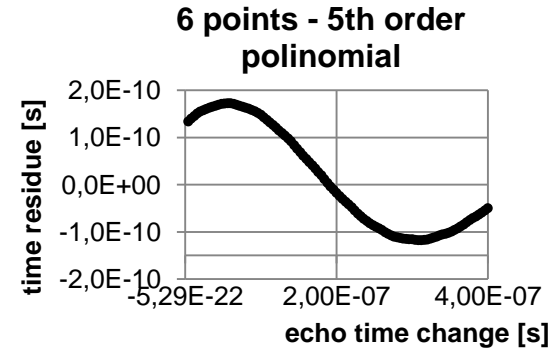
→ 2nd time resolution problem: change of echo



Prior Trial Targets:

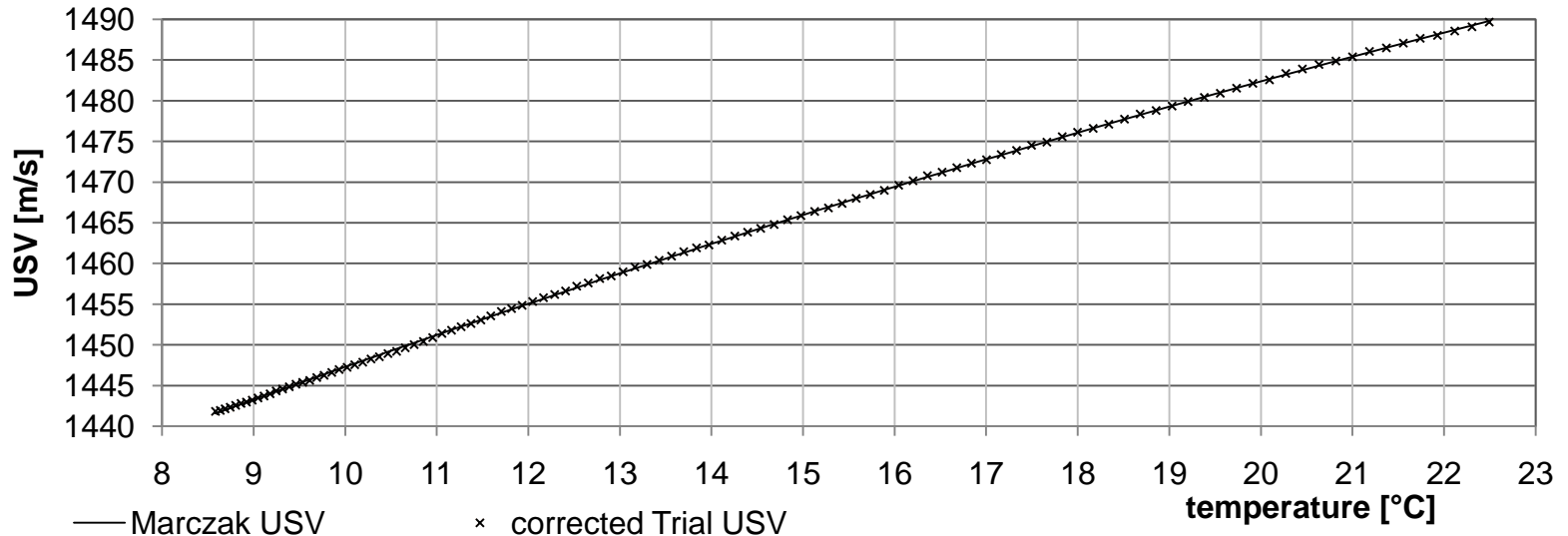
- **Absolute Error:** trials and analysis for a well known and elaborately analyzed material – WATER (Marczak, 1997)
- **Stability Analysis** for real process data (yeast propagation) → malfunctions, outliers, standard deviation

		laboratory, water 10°C	laboratory, water 15°C	laboratory, water 20°C	process, 110-119
TOF average	[s]	6.9069E-05	6.8179E-05	6.7416E-05	6.6346E-05
standard deviation	[s]	9.5716E-10	1.2457E-09	2.1864E-09	1.1653E-11
deviation	[%]	1.39E-03	1.83E-03	3.24E-03	1.76E-05



→ Target of 3.5 ns TOF maximum standard deviation can be reached.

→ USV for DN50 setup - accurate reflector distance of **49.968 mm**



Temperature	10°C		15°C		20°C	
	expansion corrected	constant distance	expansion corrected	constant distance	expansion corrected	constant distance
distance l_f [m]	4.9977E-02	4.9968E-02	4.9972E-02	4.9968E-02	4.9968E-02	4.9968E-02
TOF Trial Data [s]	6.9069E-05	6.9069E-05	6.8179E-05	6.8179E-05	6.7416E-05	6.7416E-05
USV Trial Data [m/s]	1447.152	1446.906	1465.922	1465.796	1482.384	1482.382
USV Marczak [m/s]	1447.291		1465.962		1482.382	
residues to Marczak [m/s]	0.139	0.385	0.040	0.166	-0.002	0.001
absolute error [%]	9.62E-03	2.66E-02	2.74E-03	1.13E-02	-1.20E-04	3.68E-05

$$USV(T) = \sum_{i=0}^5 (P_i \cdot T^i)$$

	Konstanten
P0	1.4023875E+03
P1	5.0388130E+00
P2	-5.7991360E-02
P3	3.2871560E-04
P4	-1.3988450E-06
P5	2.7878600E-09

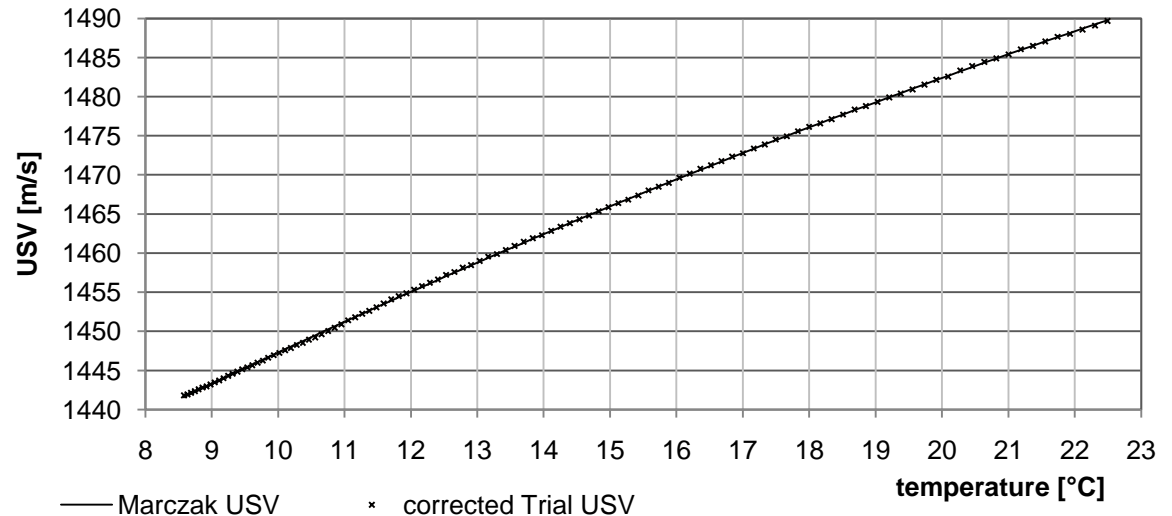
(Marczak, 1997)

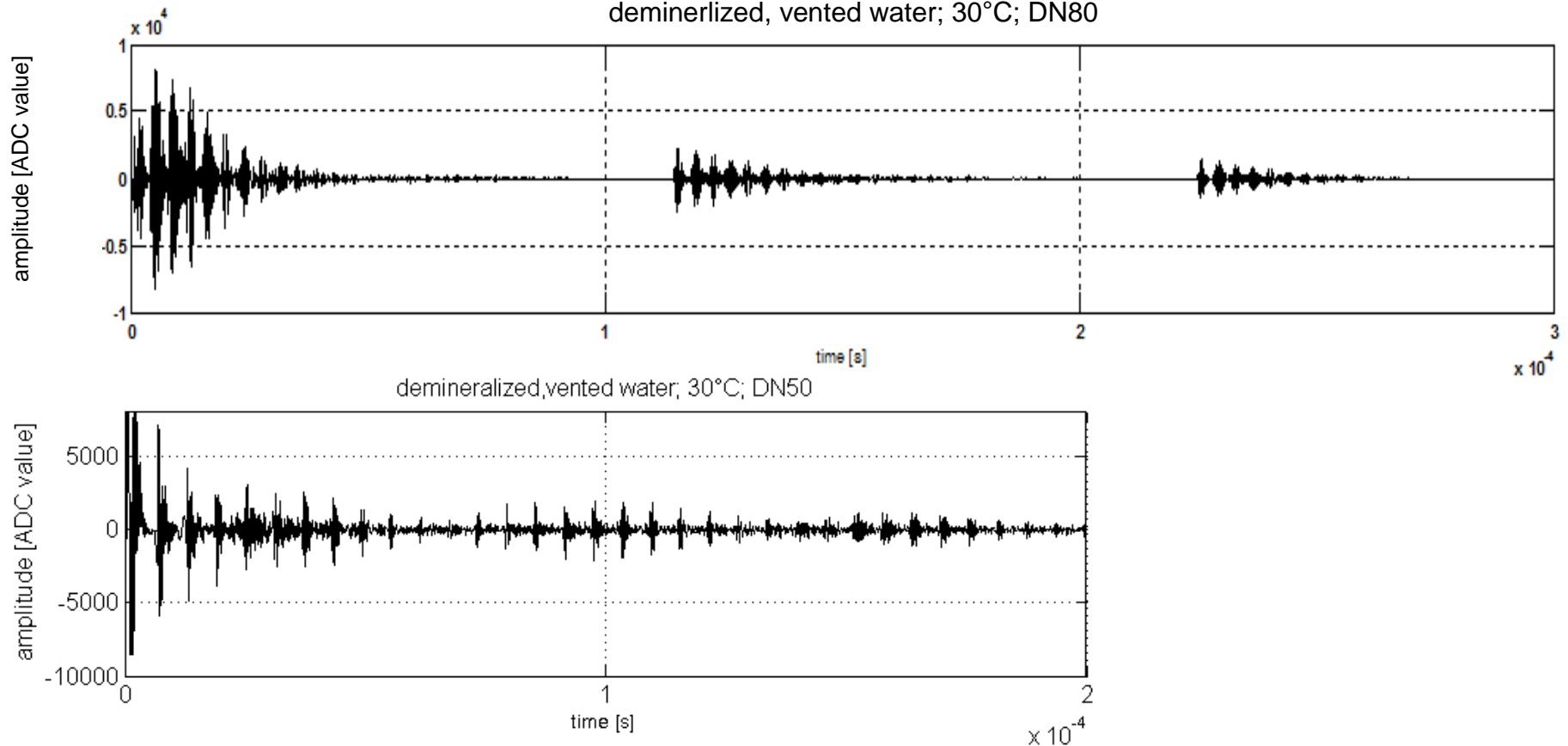
→ **Theoretical, temperature generated error for $\Delta T = 0.1$ K:**

$$\Delta USV = \frac{\partial USV(T)}{\partial T} \Delta T$$

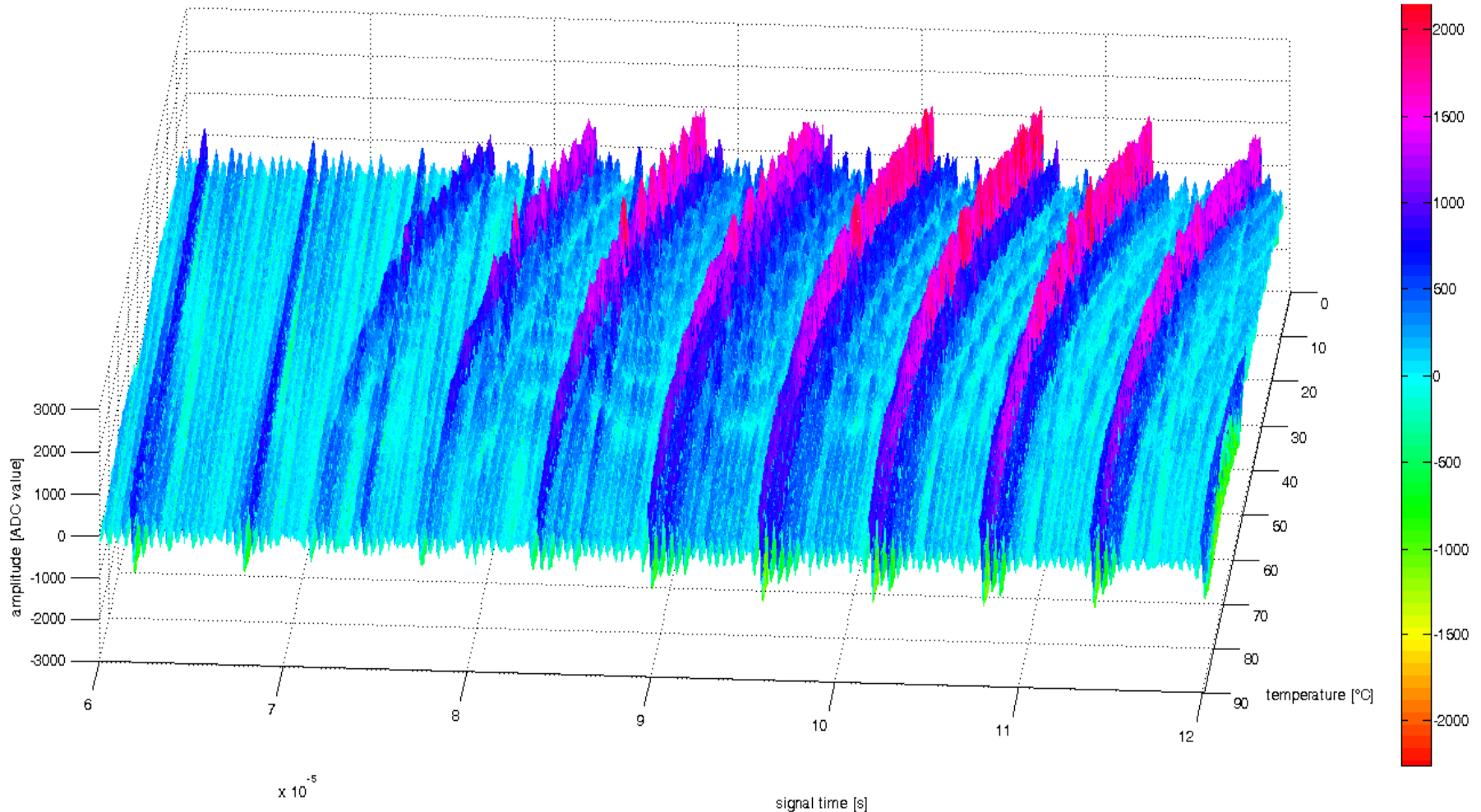
0.42 m/s (0.03%) for 8°C
0.29 m/s (0.02%) for 22°C

→ **Target: 0.075 m/s**

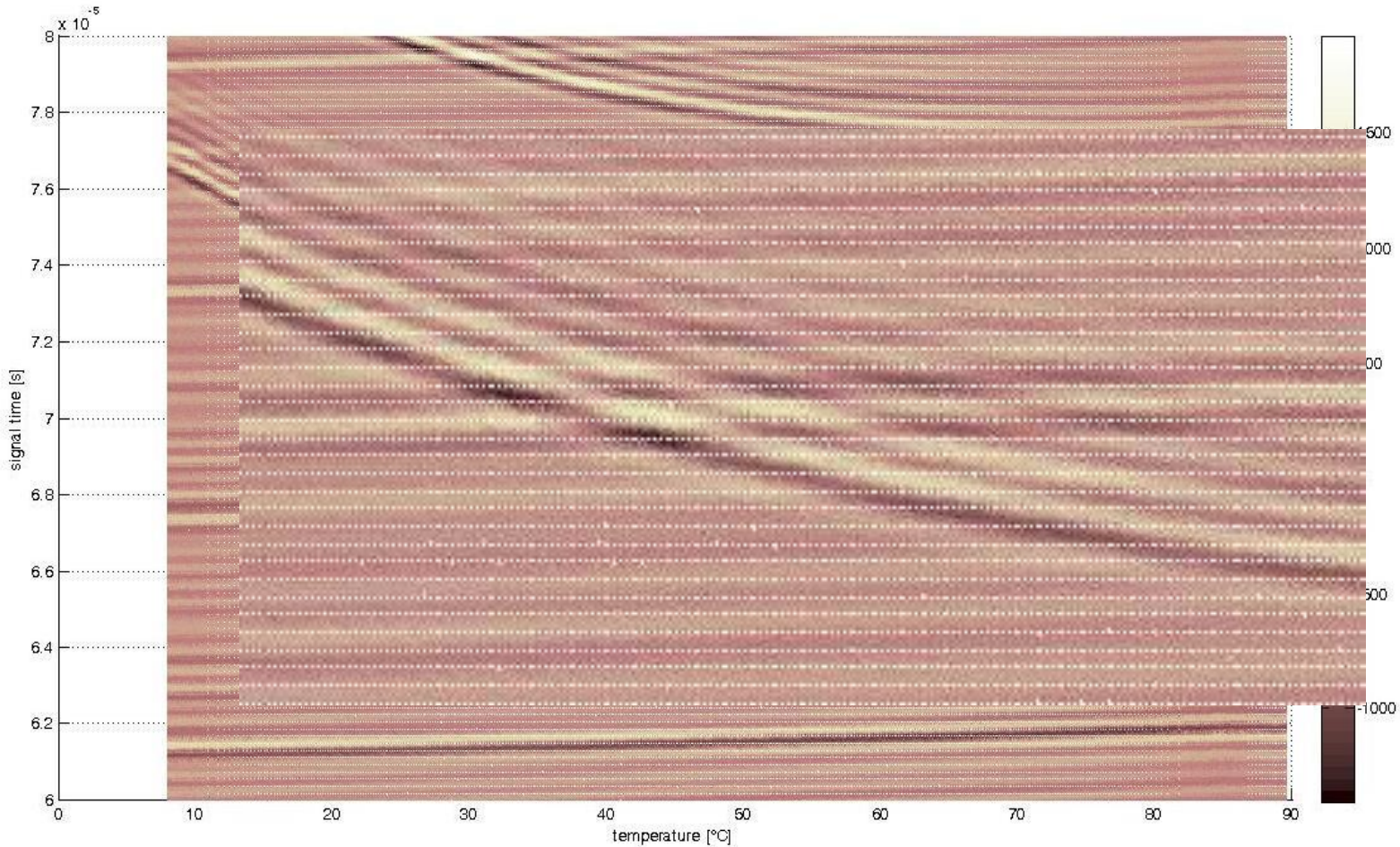




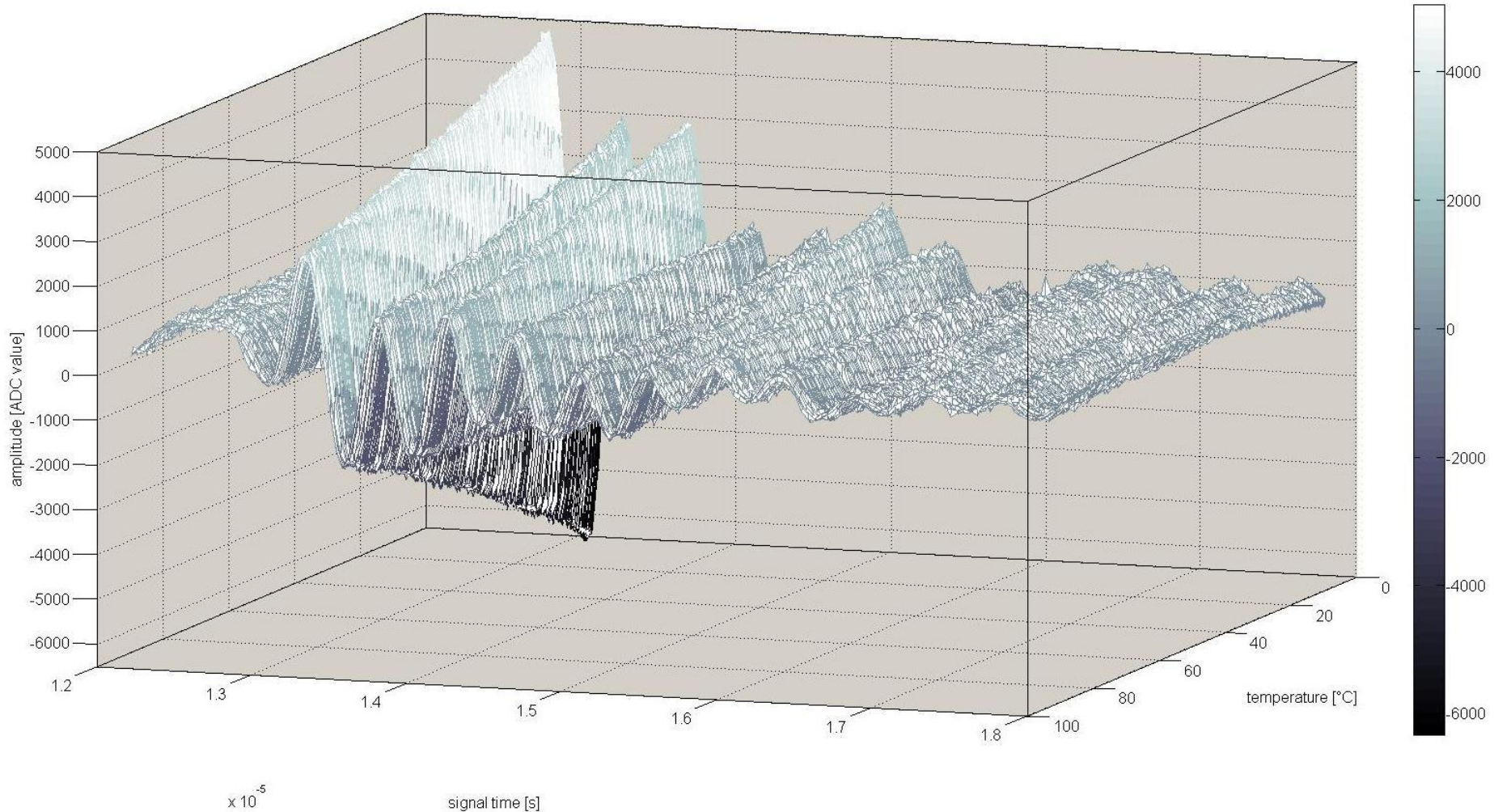
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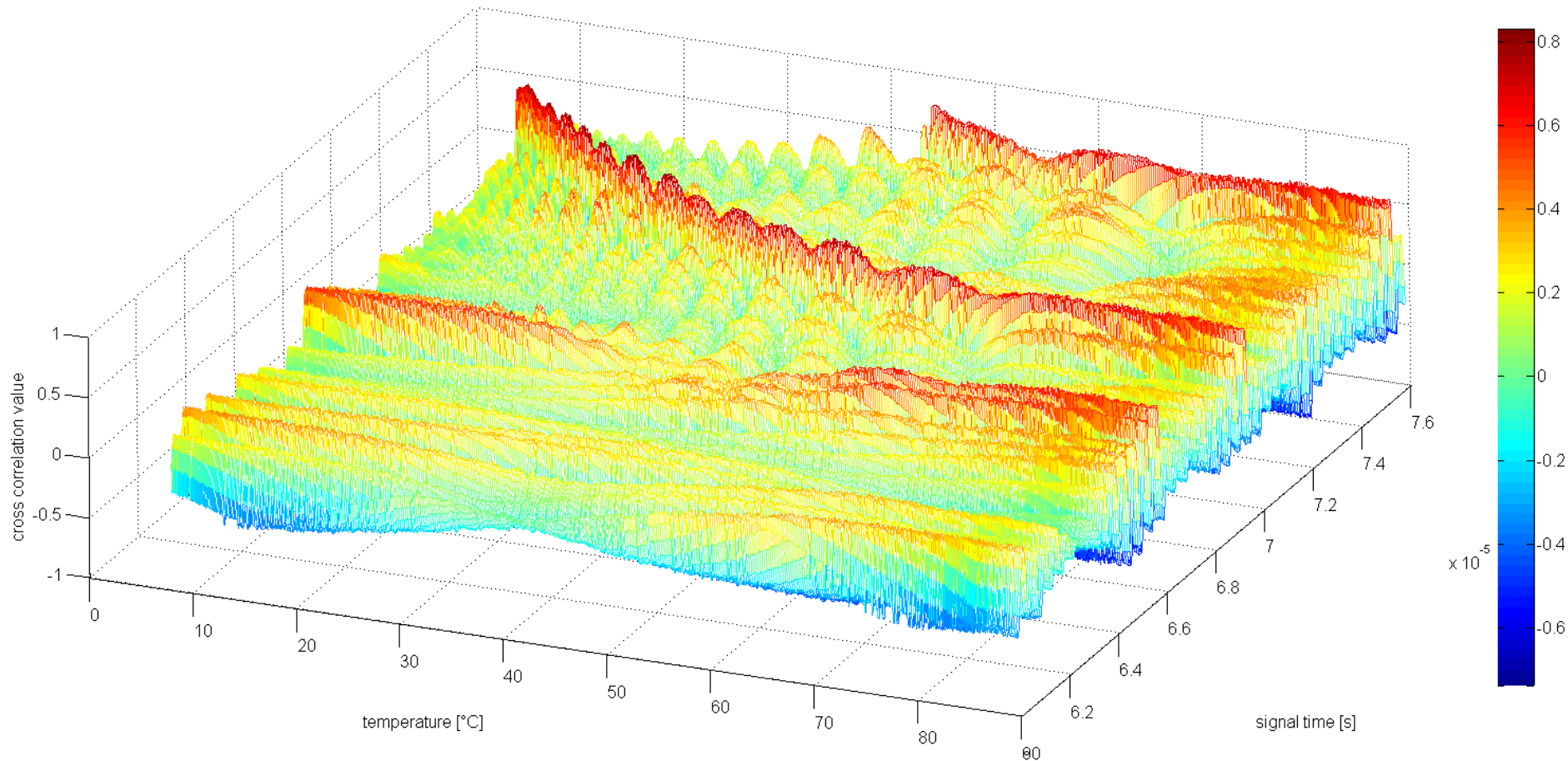


→ constructive and destructive superposition of buffer reflections and echo changes signal and thus the correlation results



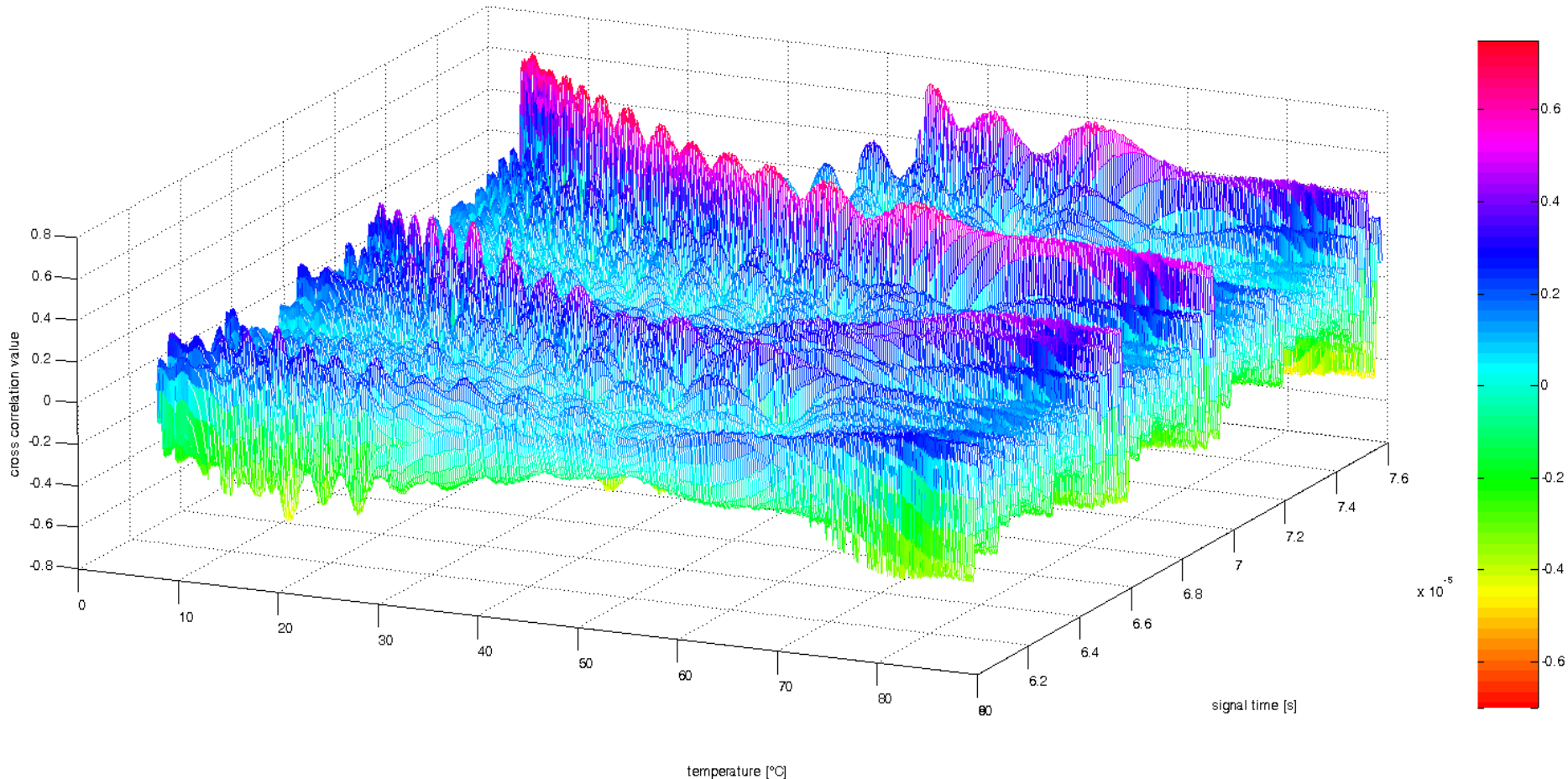
→ time change due to temperature dependent thickness expansion of buffer
→ amplitude change due to temperature dependent absorption and reflection coefficients

→ cross correlation values for demineralized, vented water; reference signal of 1 frame length (150 points)



→ no stable correlation threshold for detection can be found

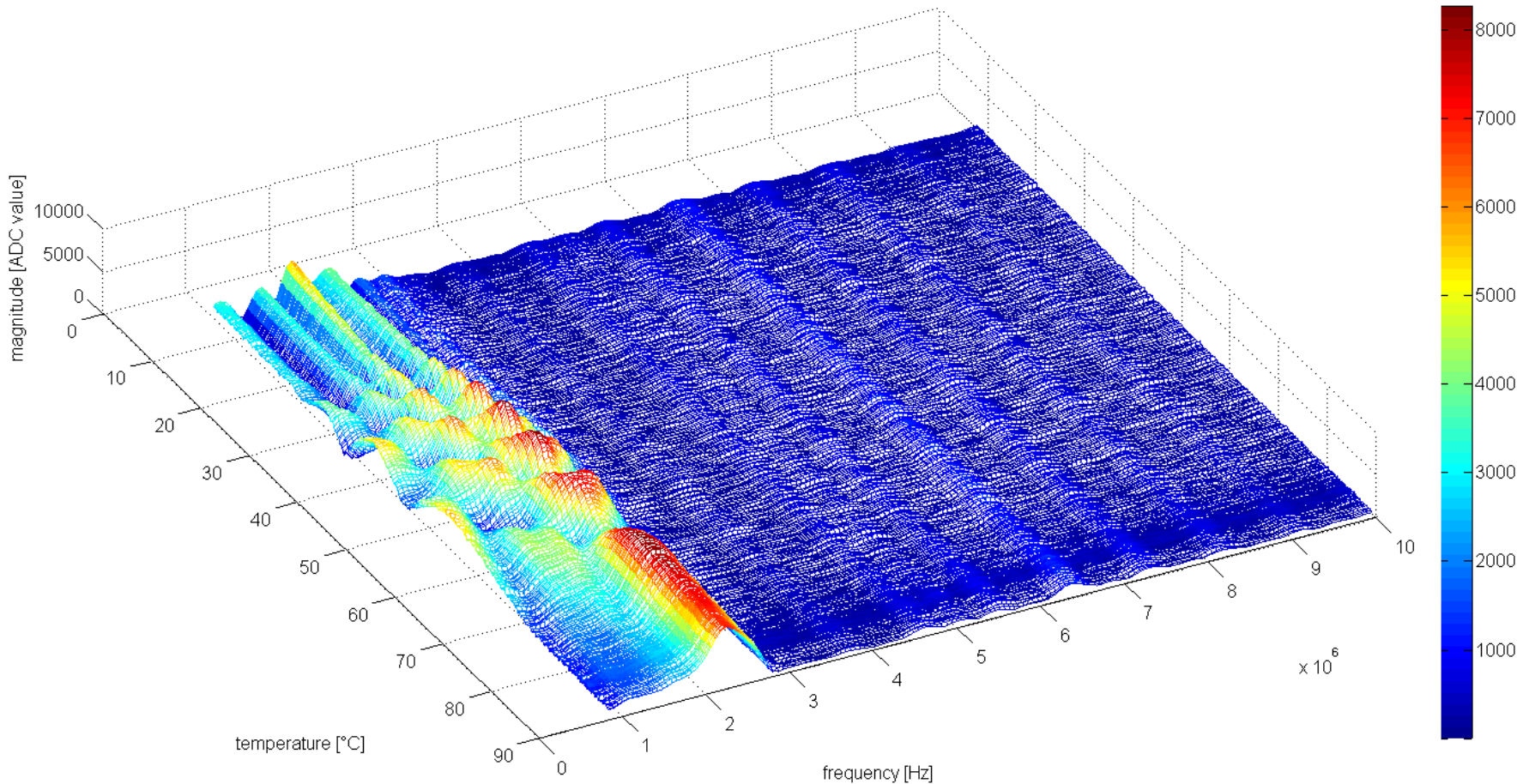
→ cross correlation values for demineralized, vented water; reference signal of triple frame length (450 points)



→ same instability

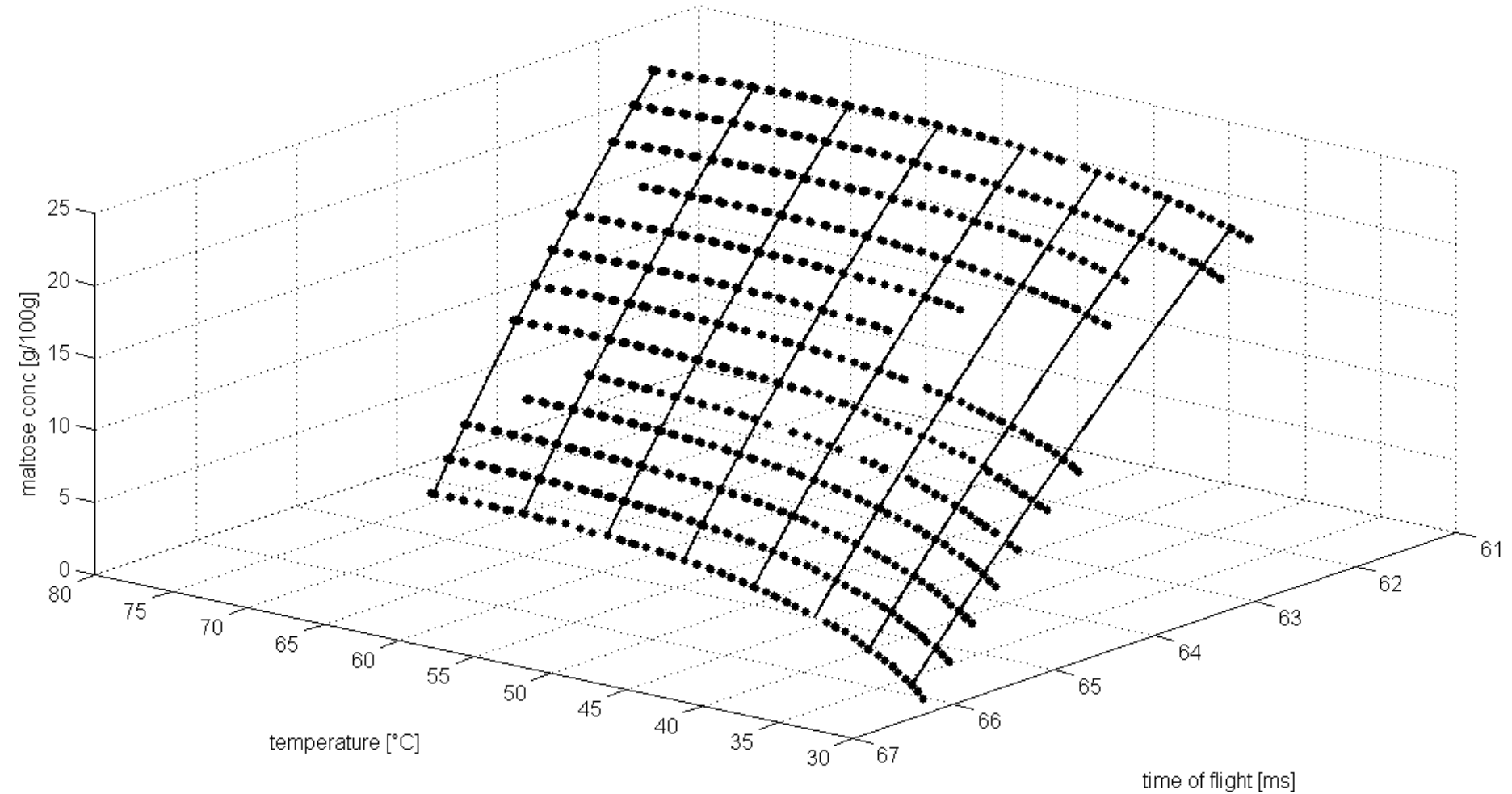
→ demineralized, vented water

Temperature dependent power spectrum for the 13th window using STFT with (0%) overlapped hann windows of length (145) points

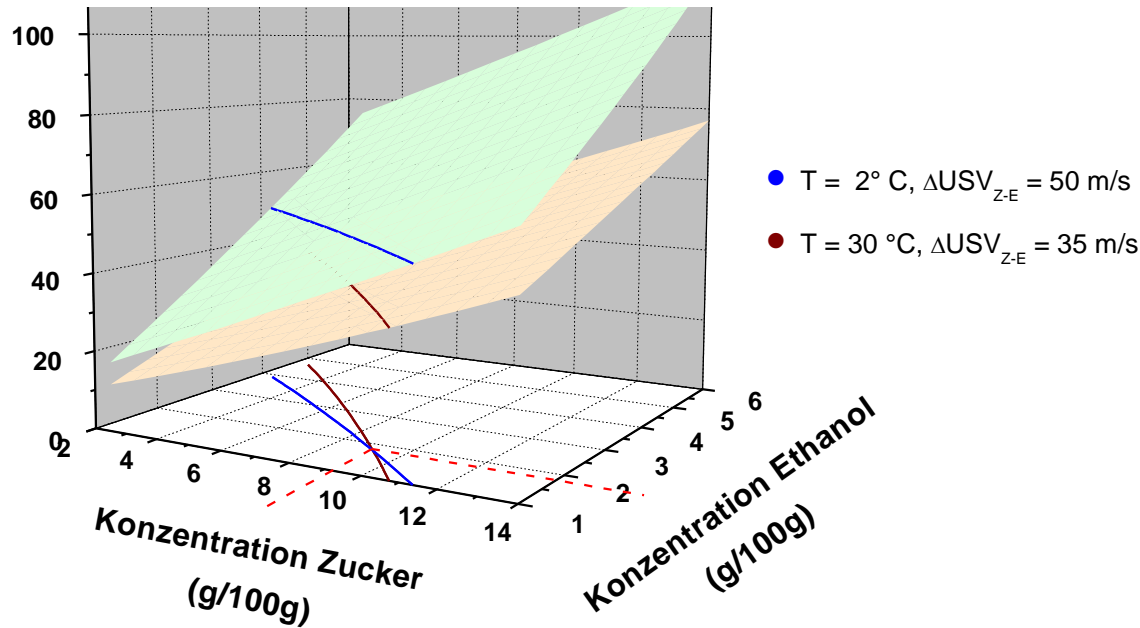


→ same up and down in the frequency domain

→ frequency domain data base will show dependency on concentration

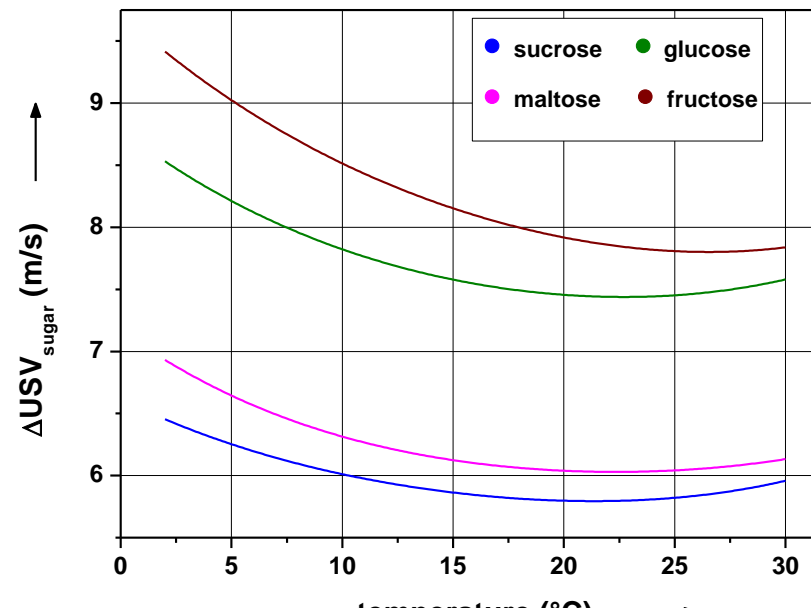


→ TOF for DN50 setup (2*49.968 mm propagation path)



→ there is no unique correlation between one temperature/ USV and one ethanol-sugar combination

→ variance due to varying rare materials can be expected



→ Process Monitoring for **Anaerobe** Yeast Fermentation:

- clear **stoichiometric ratio** between sugar and alcohol concentration (constant temperature) – model
- therefore clear concentration dependency for ultrasound velocity at one temperature

→ Process Monitoring for **Aerobe** Yeast Fermentation (Assimilation):

- modelling of stoichiometric ratio between sugar and alcohol concentration is **complex and based on experimental data**
- therefore a **third parameter** is necessary for accurate concentration determination (impedance, density, frequency domain)

- ultimate numerical solution (TOF determination) for DN50 or even less reflector distance in pulse-echo mode is quite hard; probably even impossible – **multivariate solutions** via elaborate data basis seems possible

- compromise solutions:
 - separation into relevant temperature ranges: 0-30°C, 30-70°C, 70-95°C
 - temperature dependent time threshold (functionality depends on concentration range)

- engineering solutions:
 - buffer adaption: material, thickness,...
 - reflector distance... DN80
 - transmission mode

Thanks for your Attention

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